

Monolithic sensors in ALICE

CERN



ALICE

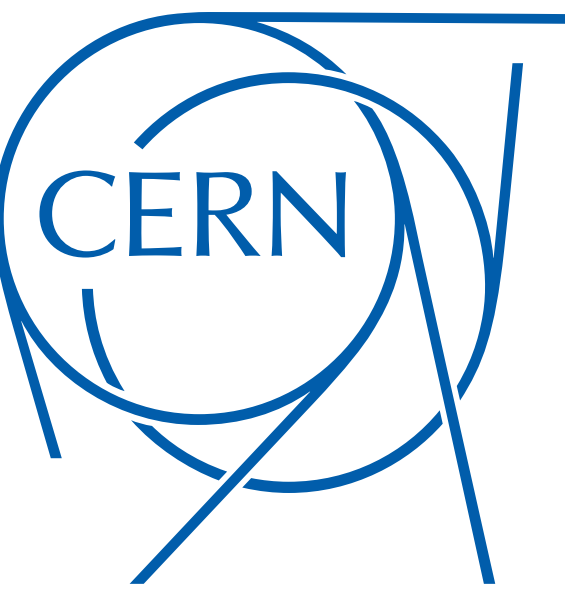
Pb-Pb 5.36 TeV

LHC22s period

18th November 2022

16:52:47.893

Magnus Mager (CERN)
DRD7 — 15.03.2023



Monolithic sensors in ALICE

ALICE ITS2:

- ▶ 7 layers
- ▶ 10 m² MAPS
- ▶ 12.5 GPixel
- ▶ installed in Sep'21 (LHC LS2)



ALICE

Pb-Pb 5.36 TeV

LHC22s period
18th November 2022

16:52:47.893

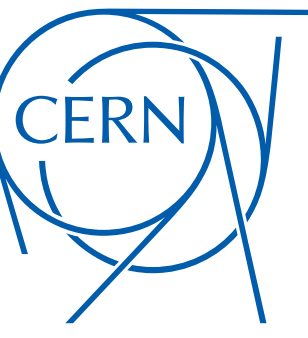
Magnus Mager (CERN)
DRD7 — 15.03.2023

Executive summary

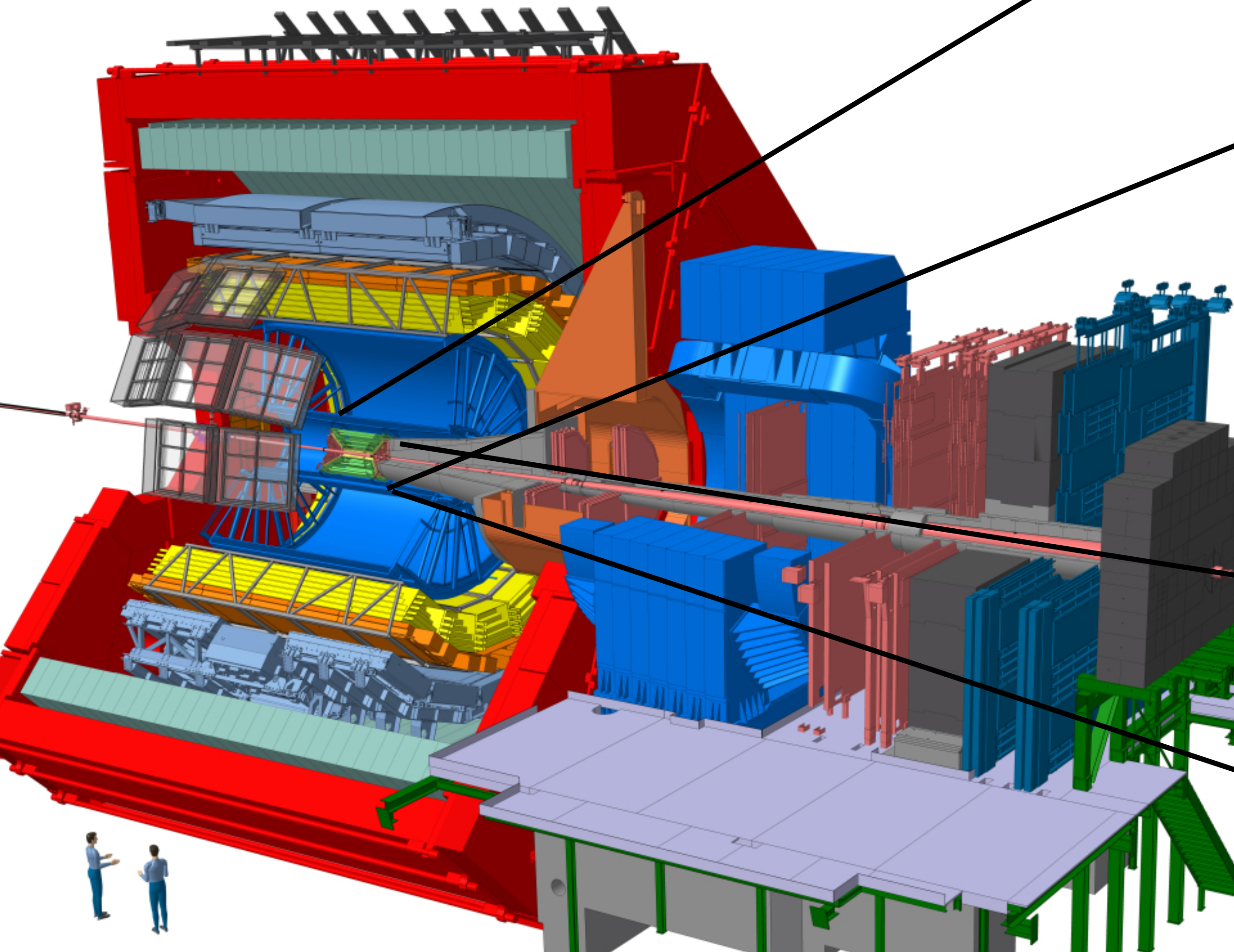


- ▶ **ALICE** is pushing **MAPS** technology since some 10 years:
 - **expertise** in design, characterisation, integration is built up at several institutes within the collaboration
 - **large workforce** >100 people, >20 institutes participate
 - long-standing **relation** with the foundry
- ▶ Driven by clear goals and timelines:
 - **ITS2+MFT** (LHC LS2, 2021): new 10 m² 7-layer monolithic Inner Tracking System and Forward Muon Tracker Tower Semiconductor 180 nm CIS (ALPIDE)
 - **ITS3** (LHC LS3, 2028): new inner-most 3 layers, wafer-scale, bent, stitched sensors Tower Partner Semiconductor 65 nm CIS
 - **ALICE 3** (LHC LS4, 2034): 60 m² silicon-only vertexer and tracker Tower Partner Semiconductor 65 nm CIS (baseline, tbc)
- ▶ R&D is exploring the technology far beyond the strict ALICE needs:
 - e.g. using process options to improve on radiation hardness and timing performance
 - gives a lot of **confidence** for the concrete ALICE application, **serves** the community as a whole, and also paves the way for the **future** ALICE plans
- ▶ Developed technology is used for several **off-spring** experiments (HEP, medical, ...)
 - several (smaller, but not necessarily small) experiments have adopted ALPIDE
 - 180 nm technology is now widely used

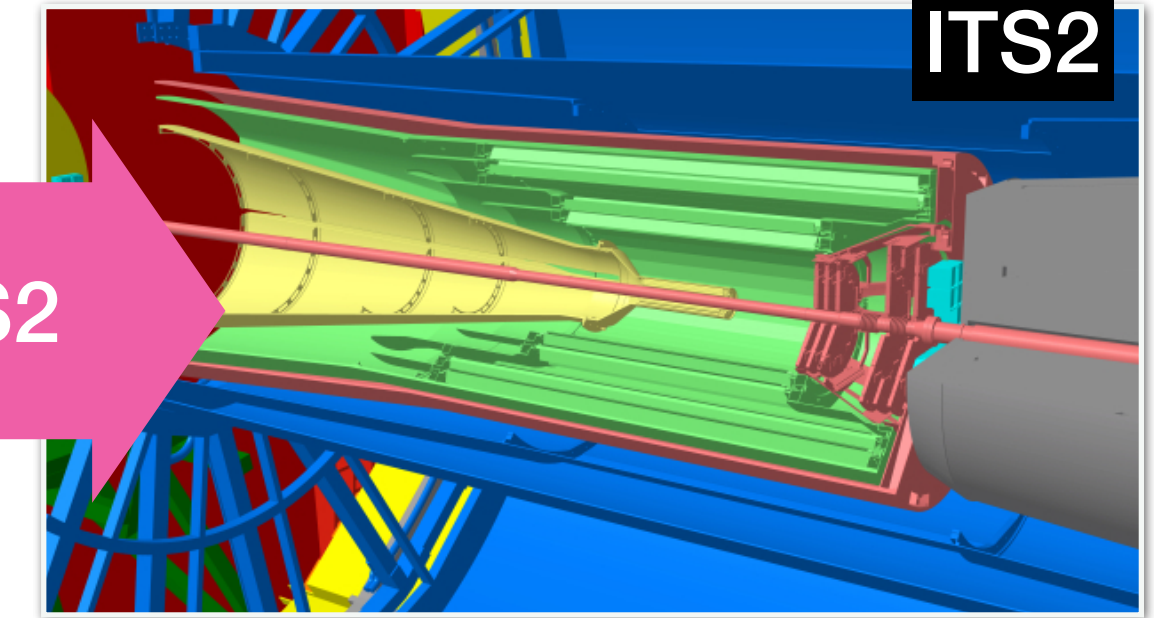
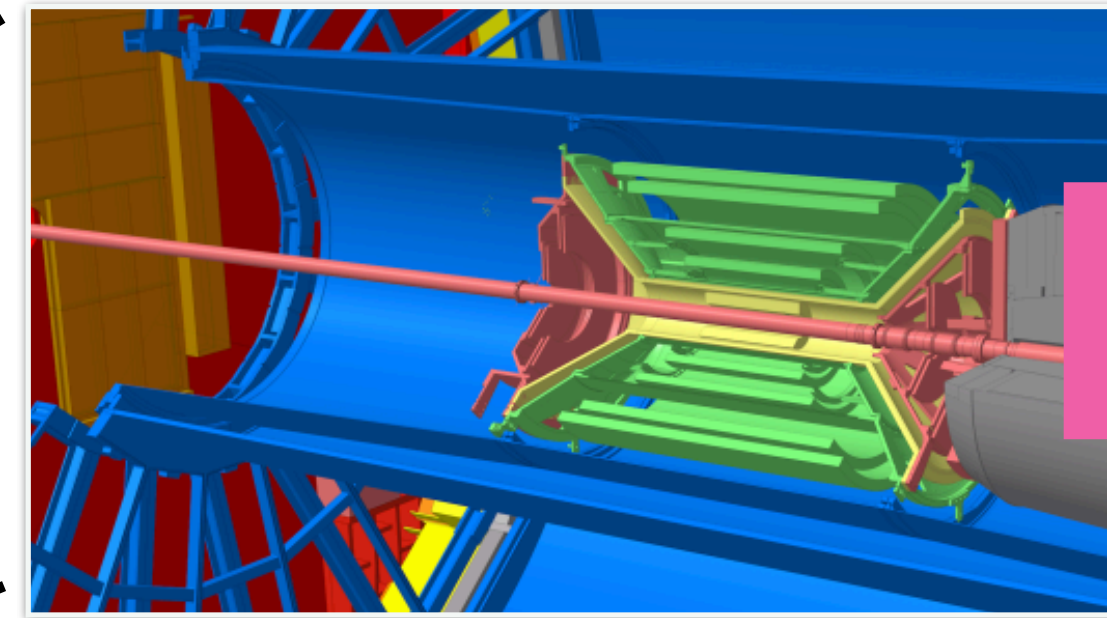
ITS2+MFT



ALICE LS2 upgrades with Monolithic Active Pixel Sensors (MAPS)



Inner Tracking System



6 layers:

- 2 hybrid silicon pixel
- 2 silicon drift
- 2 silicon strip

Inner-most layer:

- radial distance: 39 mm
- material: $X/X_0 = 1.14\%$
- pitch: $50 \times 425 \mu\text{m}^2$
- rate capability: 1 kHz

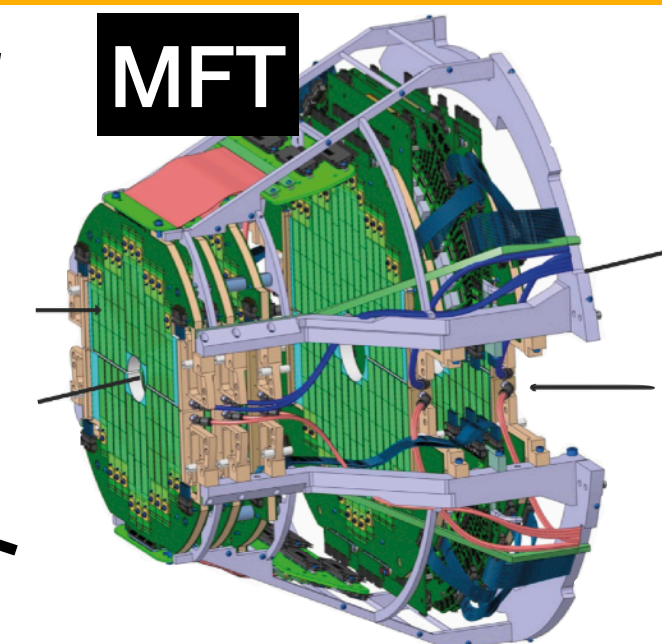
7 layers:

- all MAPS
- 10 m², 24k chips, 12.5 Giga-Pixels

Inner-most layer:

- radial distance: 23 mm
- material: $X/X_0 = 0.35\%$
- pitch: $29 \times 27 \mu\text{m}^2$
- rate capability: 100 kHz (Pb-Pb)

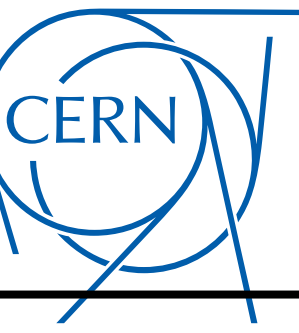
Muon Forward Tracker



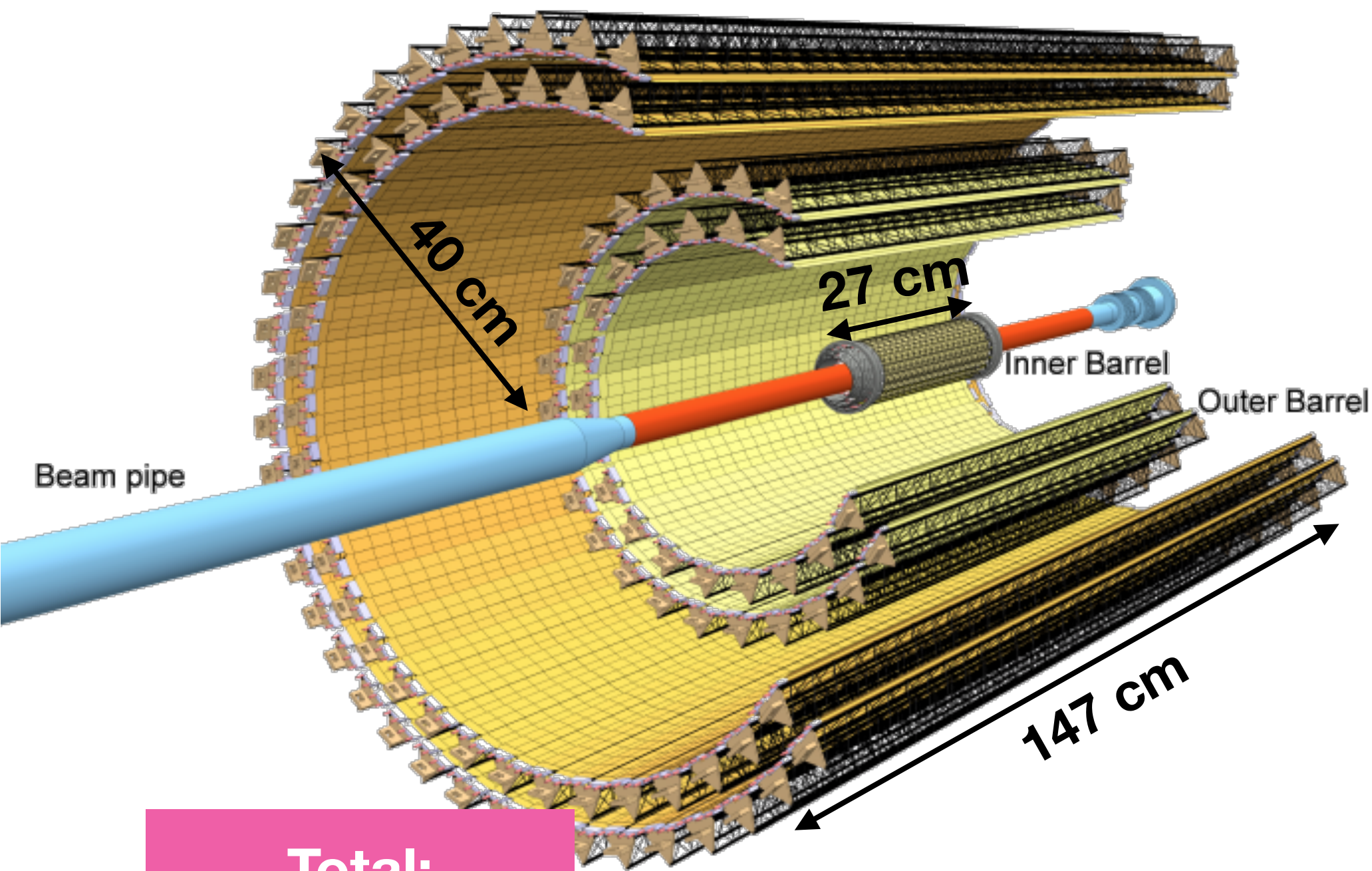
new detector

5 discs, double sided:
based on same technology as ITS2

ITS2: overview



Layout

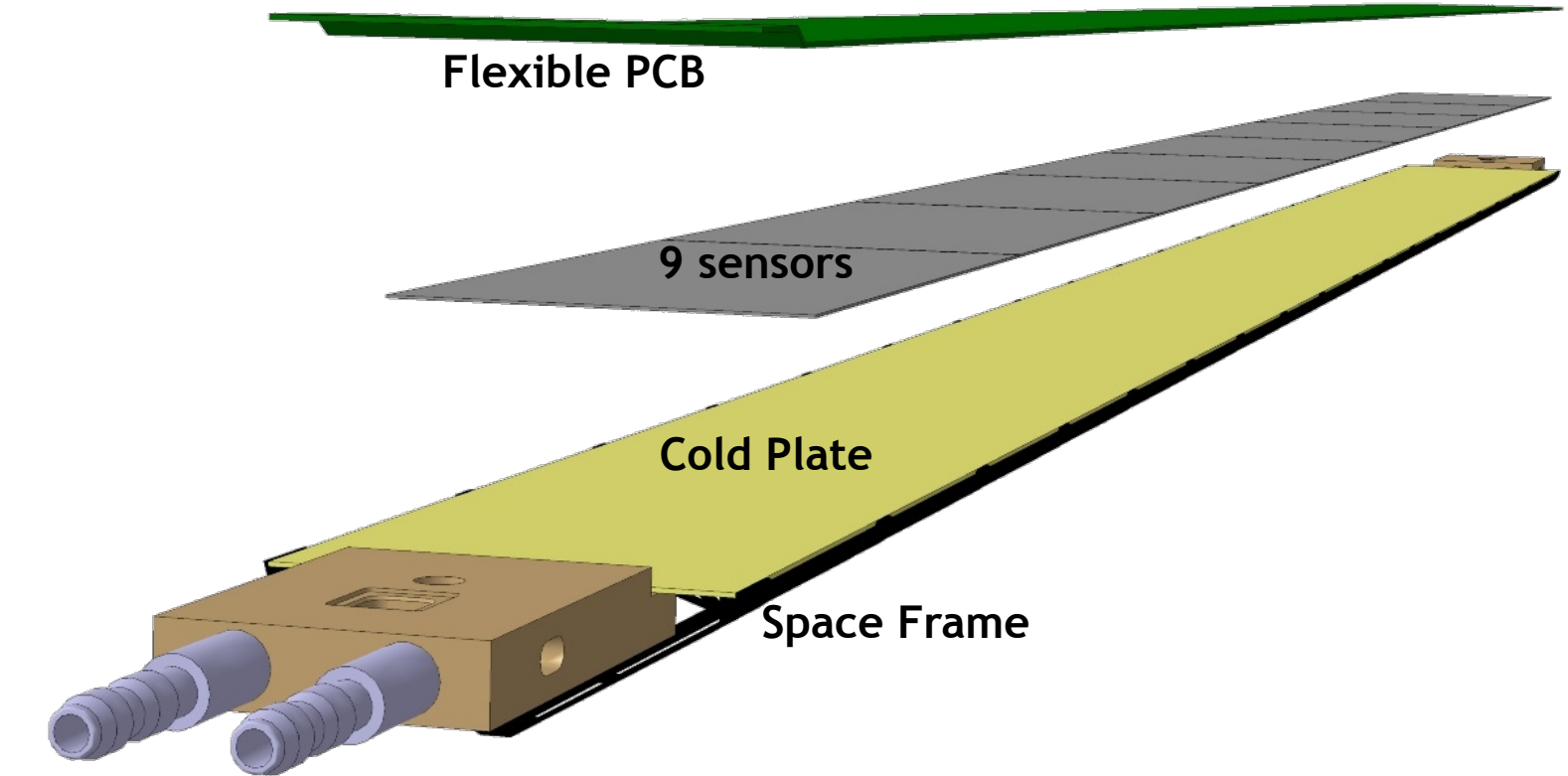


Inner Barrel (IB)

3 Inner Layers: 12+16+20 Staves
1 Module / Stave

9 sensors per Module

96 Modules to be produced
(including one spare barrel)



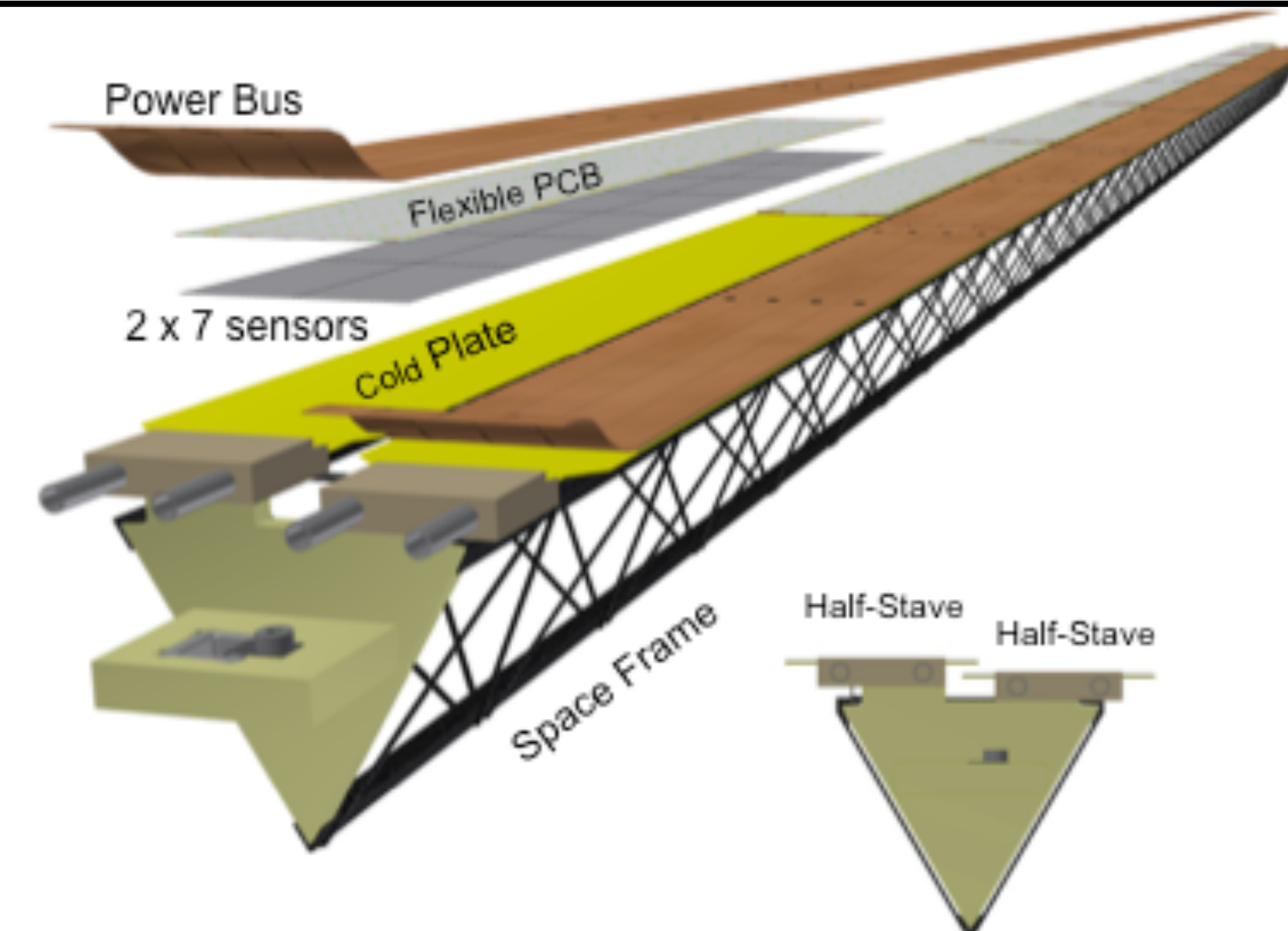
Outer Barrel (OB)

2 Middle Layers: 30+24 Staves
2x4 Modules / Stave

2 Outer Layers: 42+48 Staves
2x7 Modules / Stave

2x7 sensors / Module
(Middle and Outer Layers are equipped with the same Module Type)

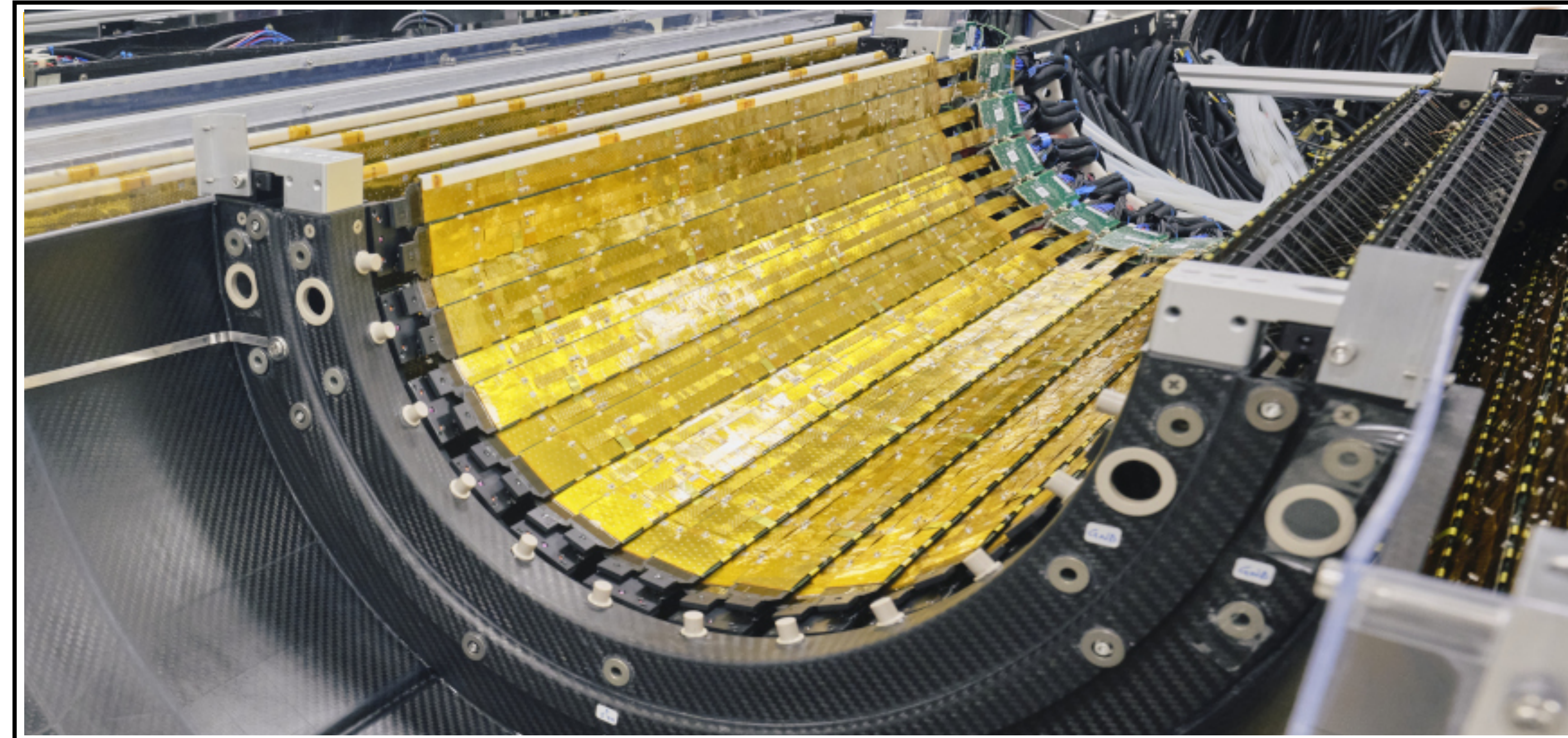
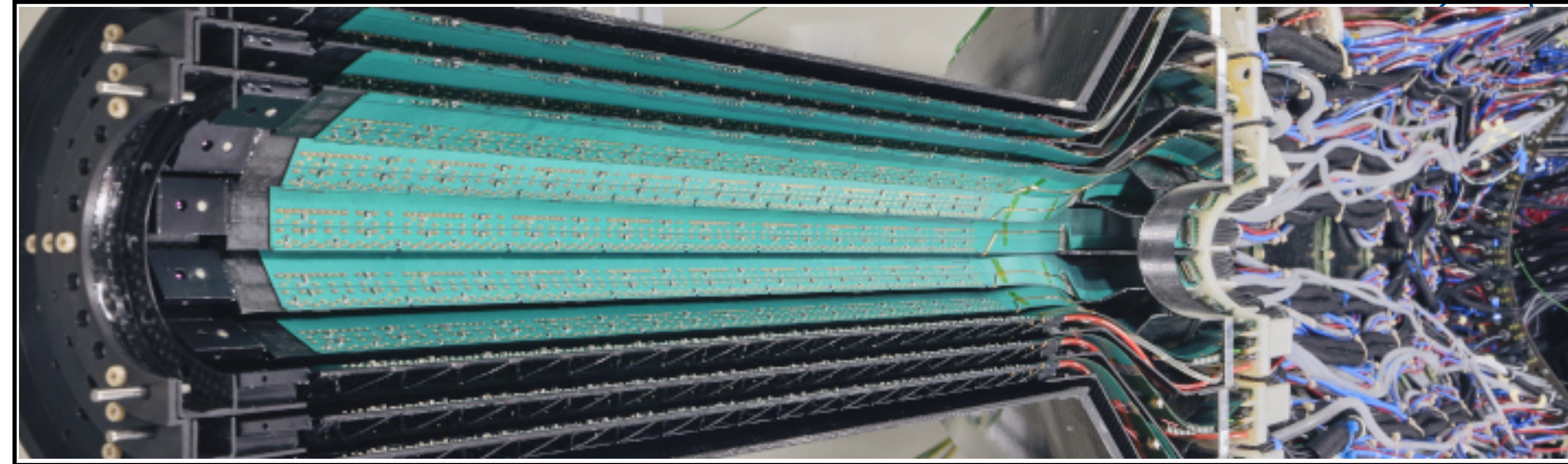
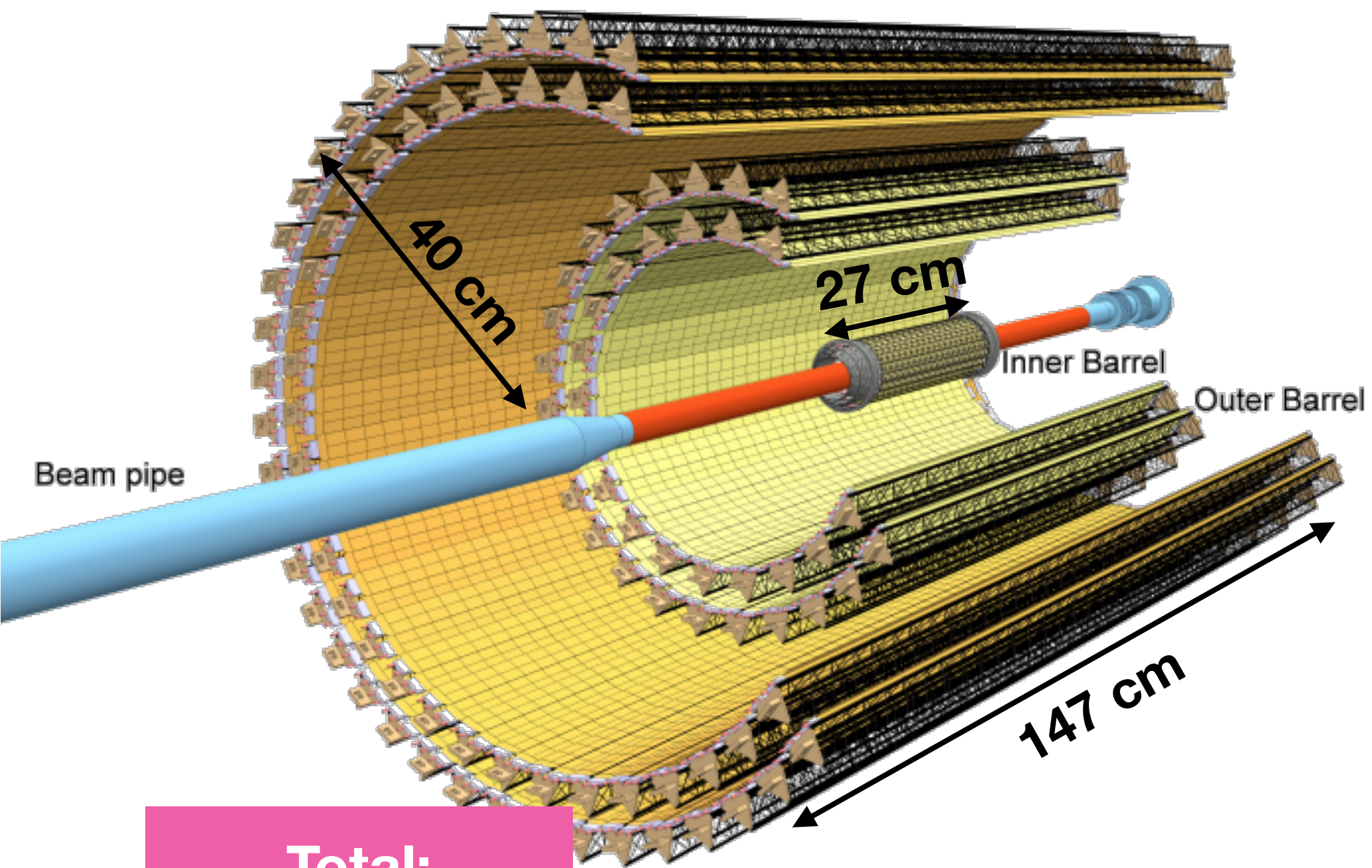
1880 Modules to be produced
(including spares)



Total:
 - 24k chips
 - 10 m²
 - 12.5 GPixel

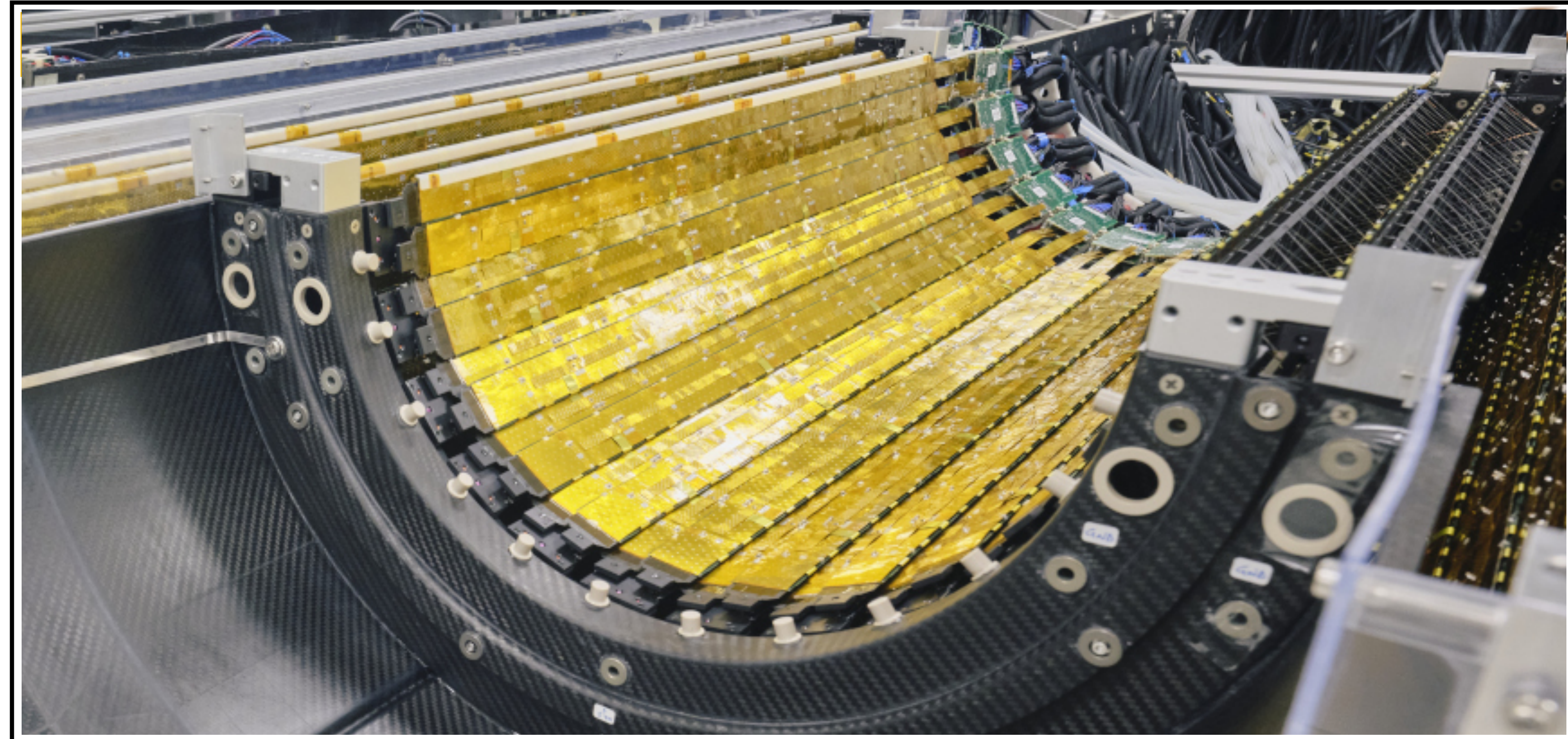
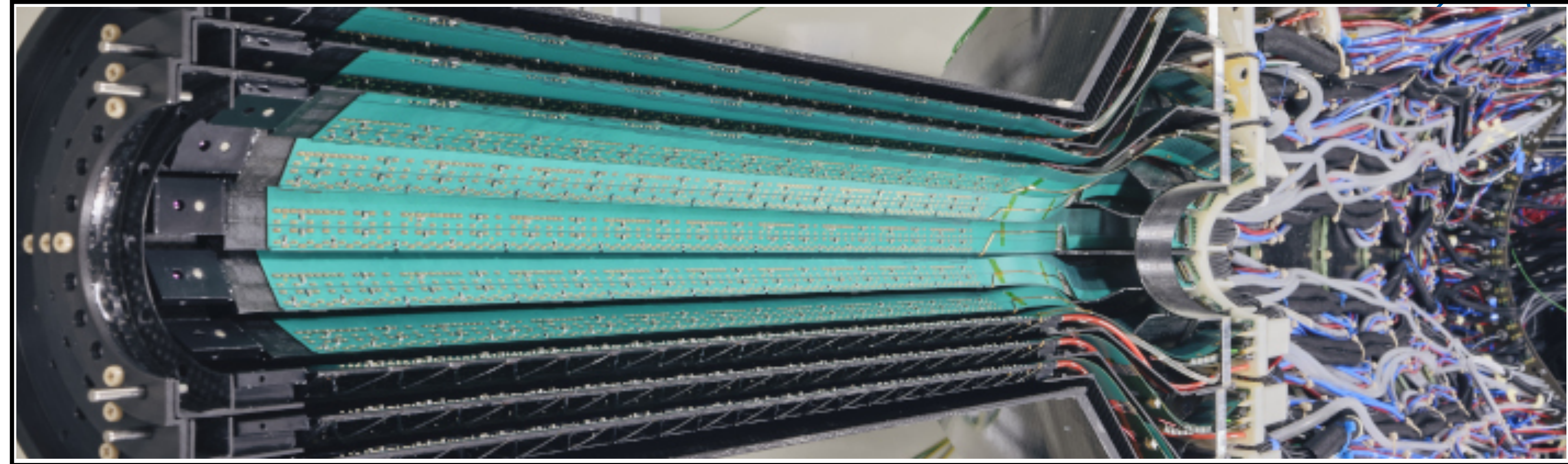
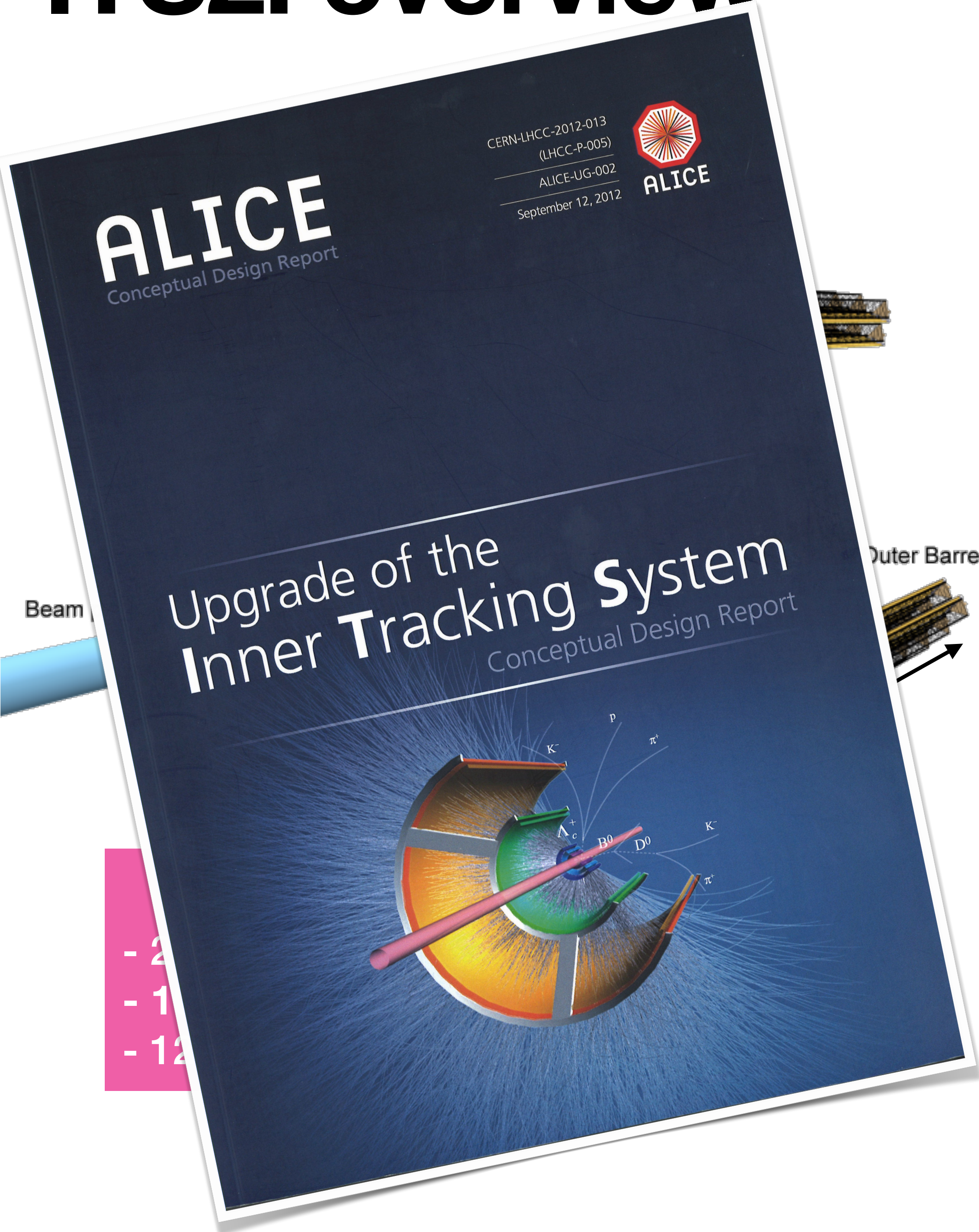
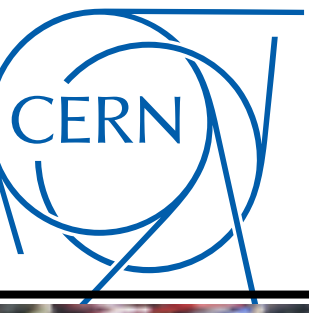
ITS2: overview

Layout

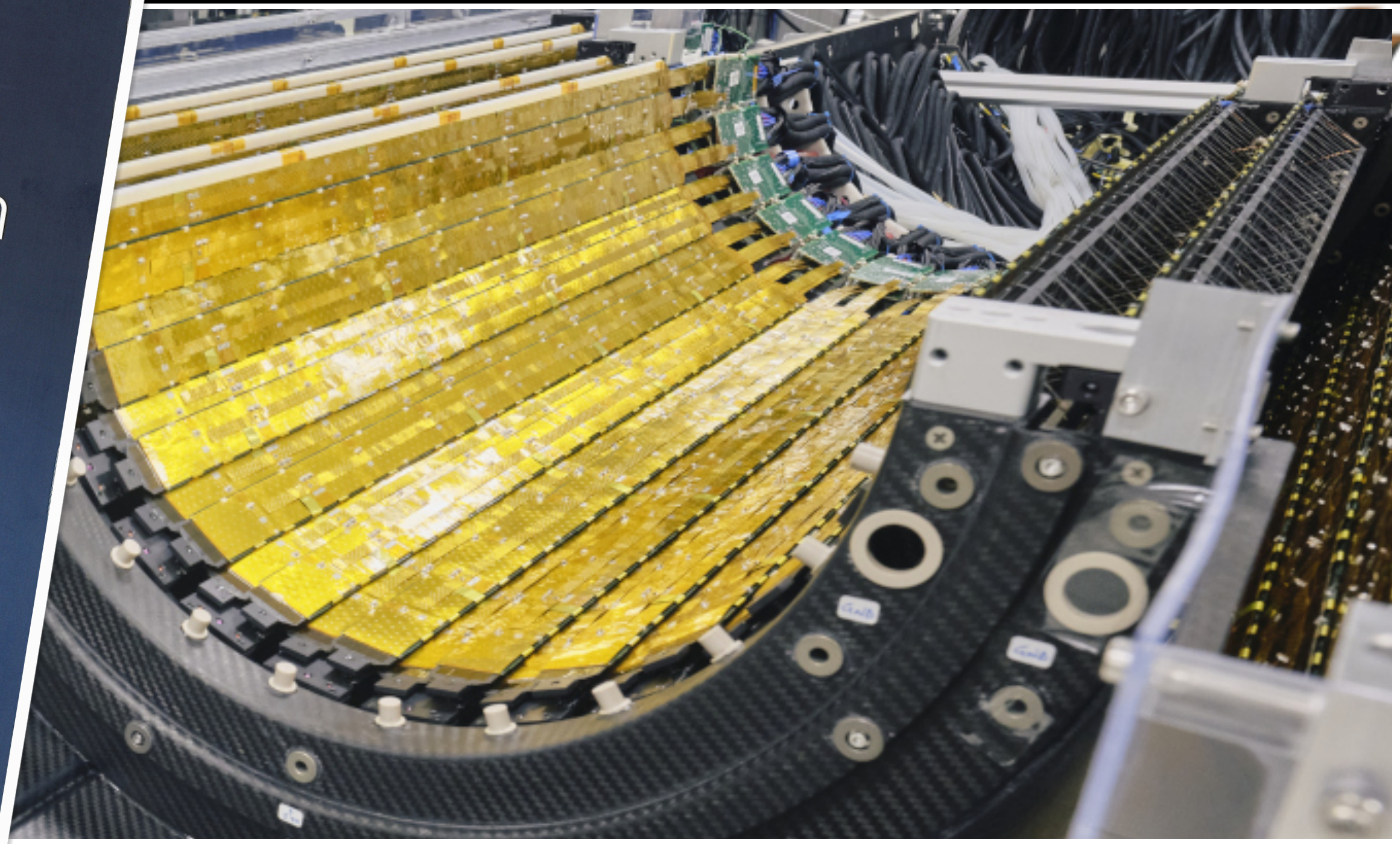
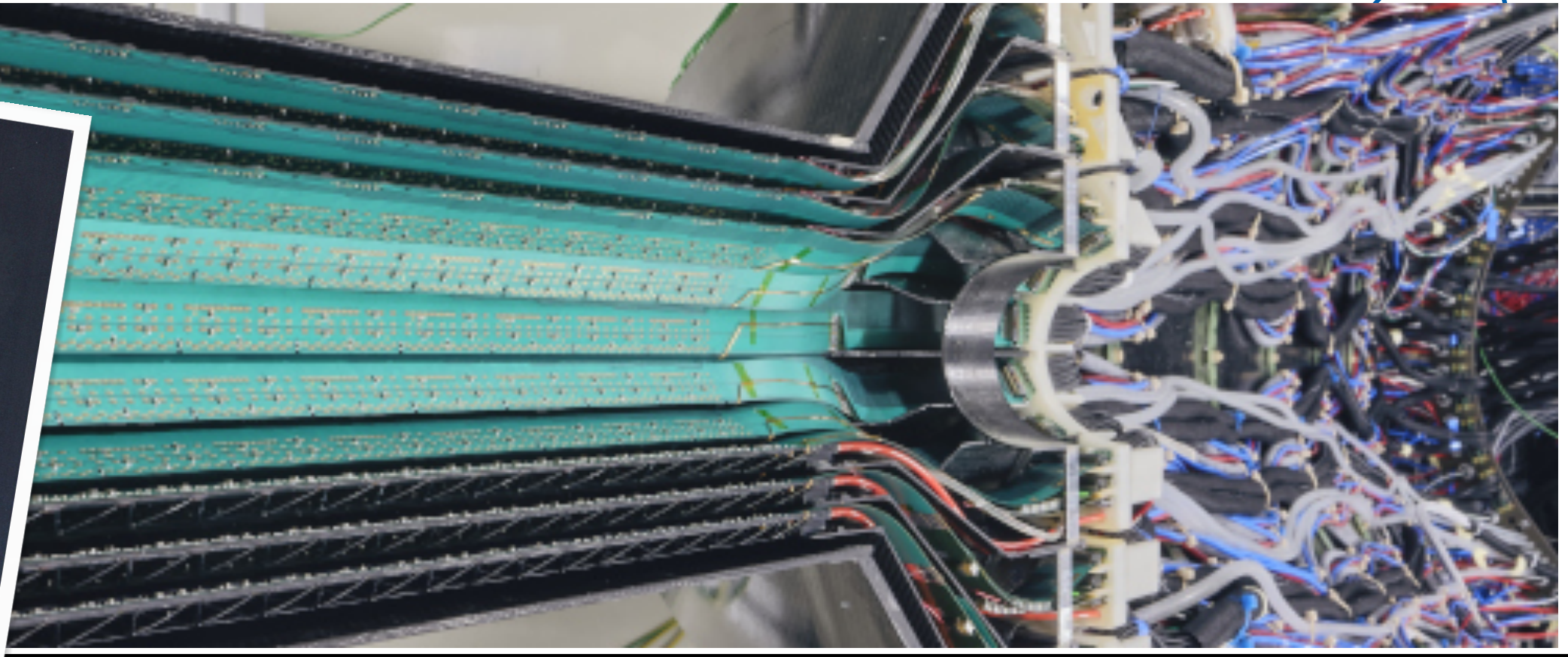
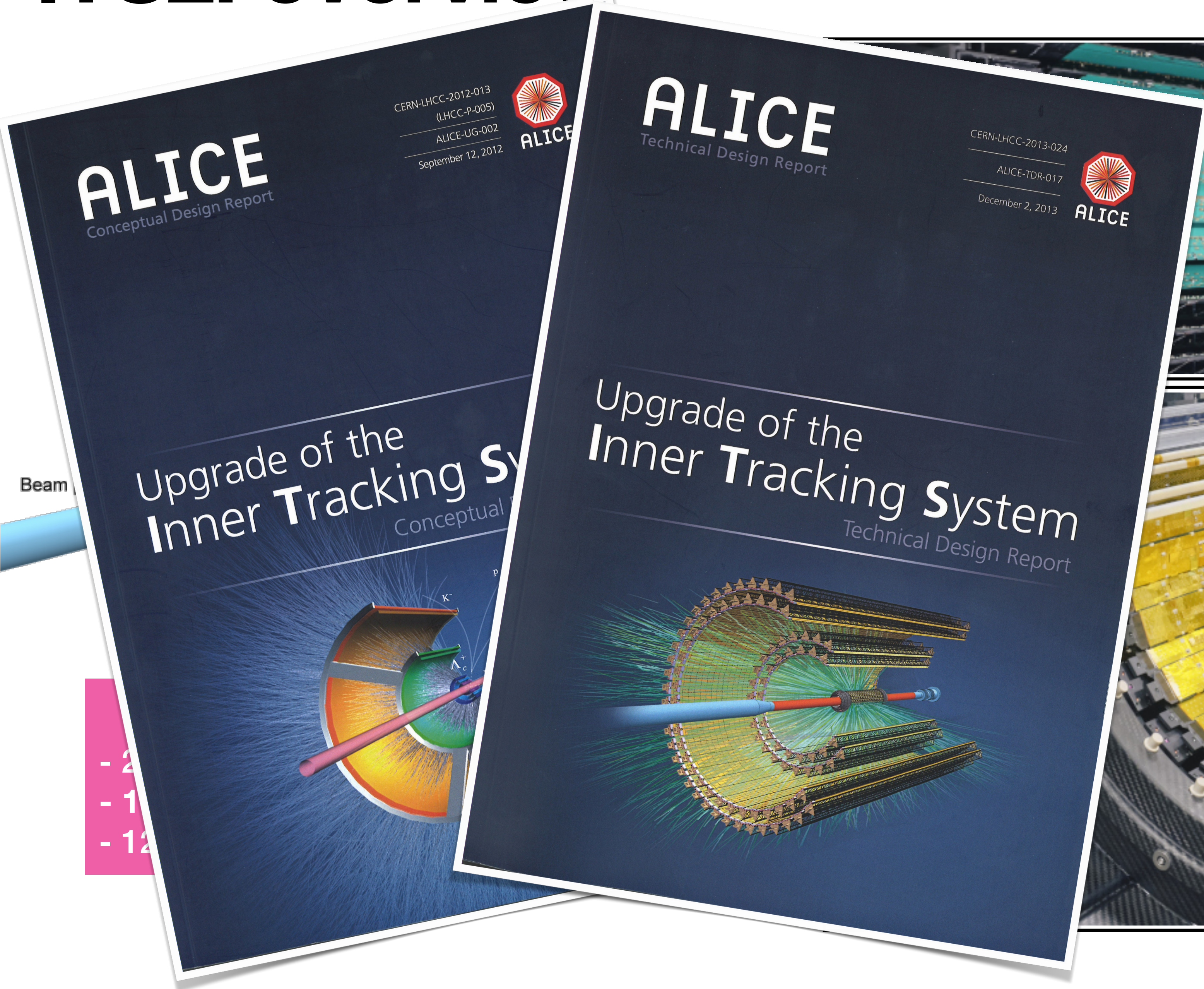
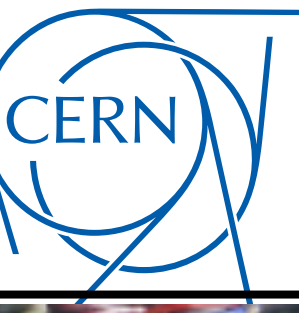


- Total:**
- 24k chips
 - 10 m²
 - 12.5 GPixel

ITS2: overview

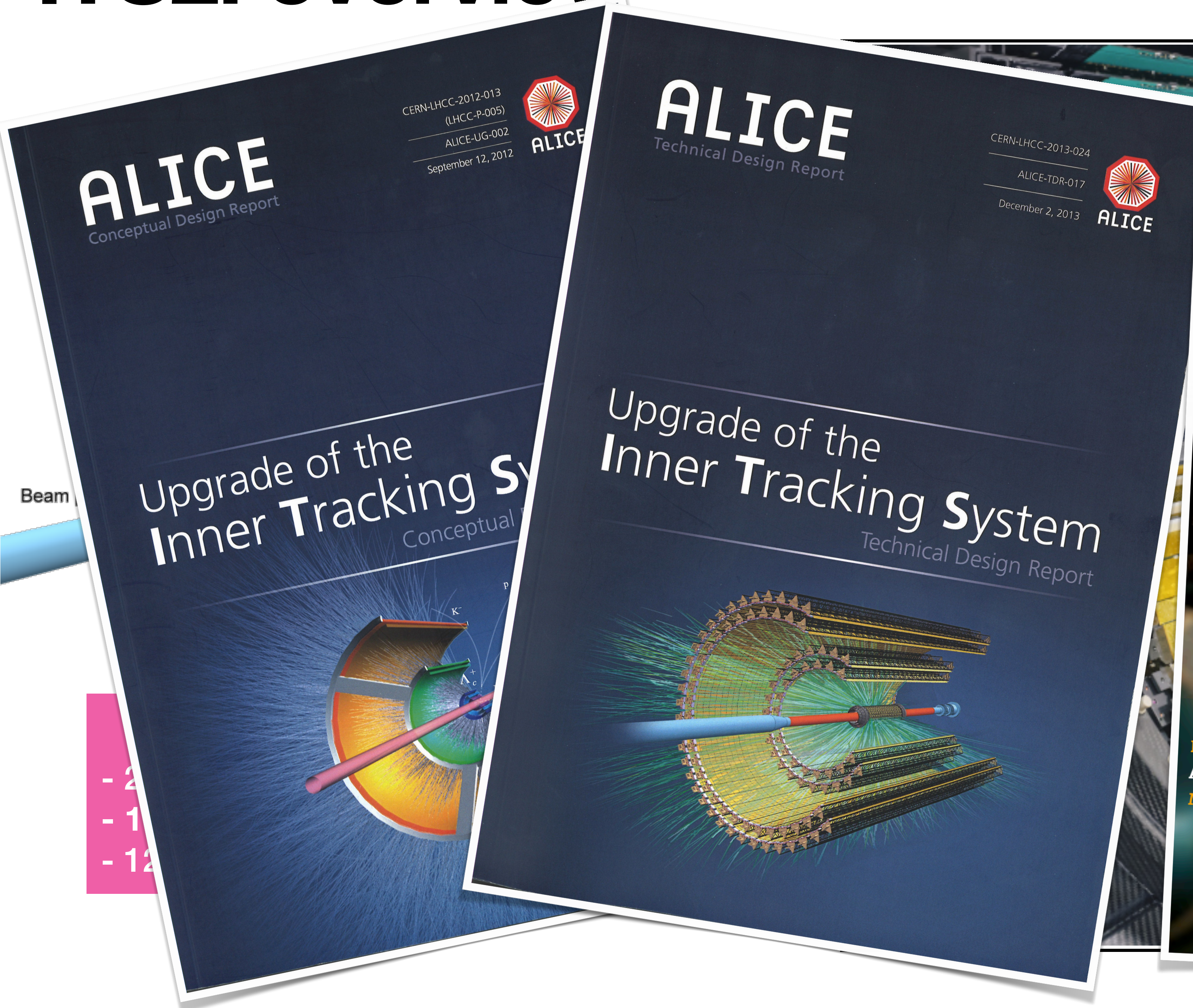


ITS2: overview



- 2
- 1
- 12

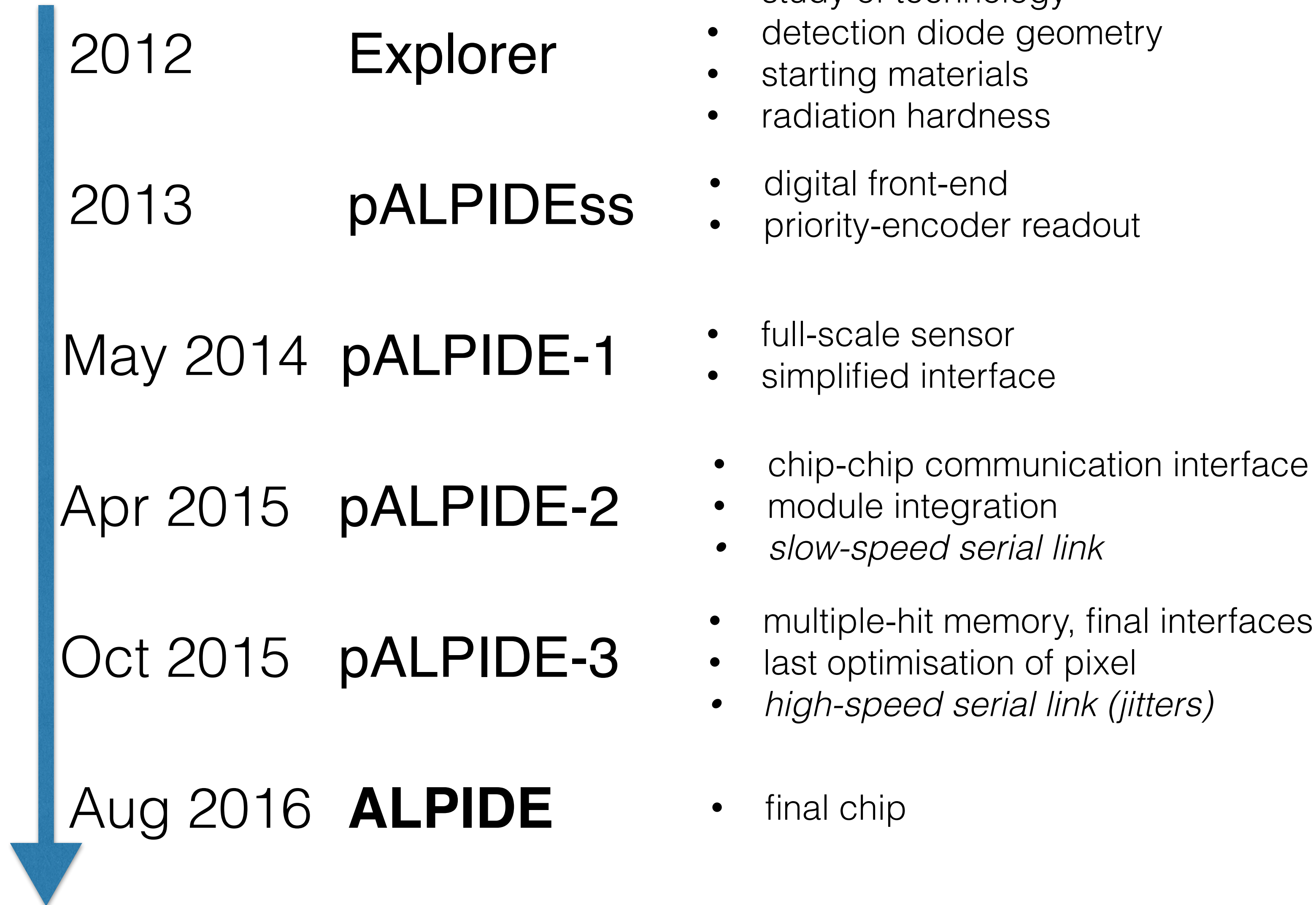
ITS2: overview



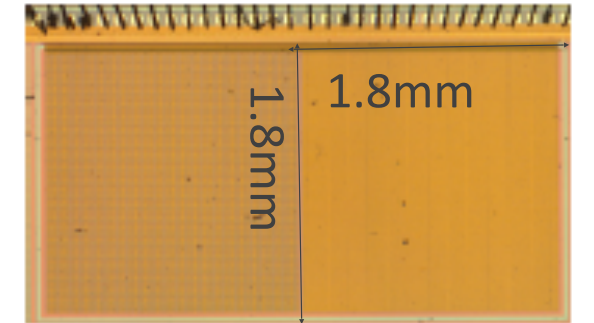
ITS2: sensor development



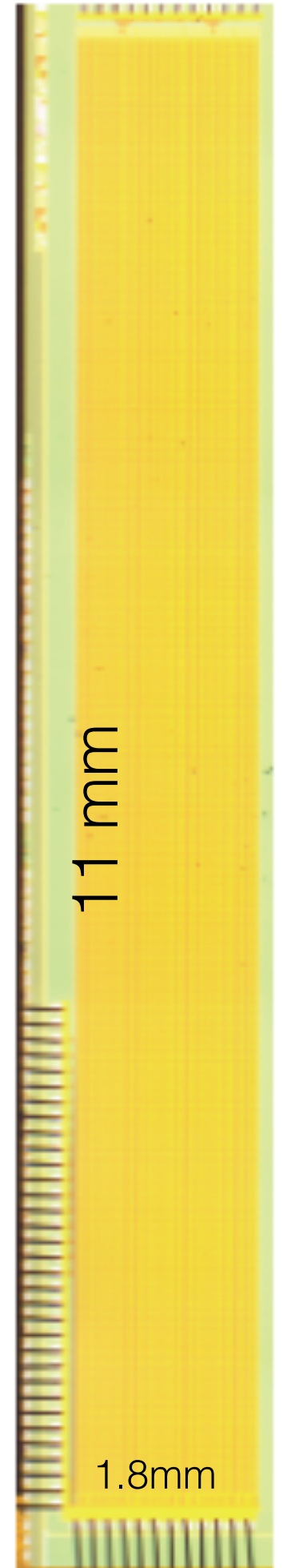
R&D path



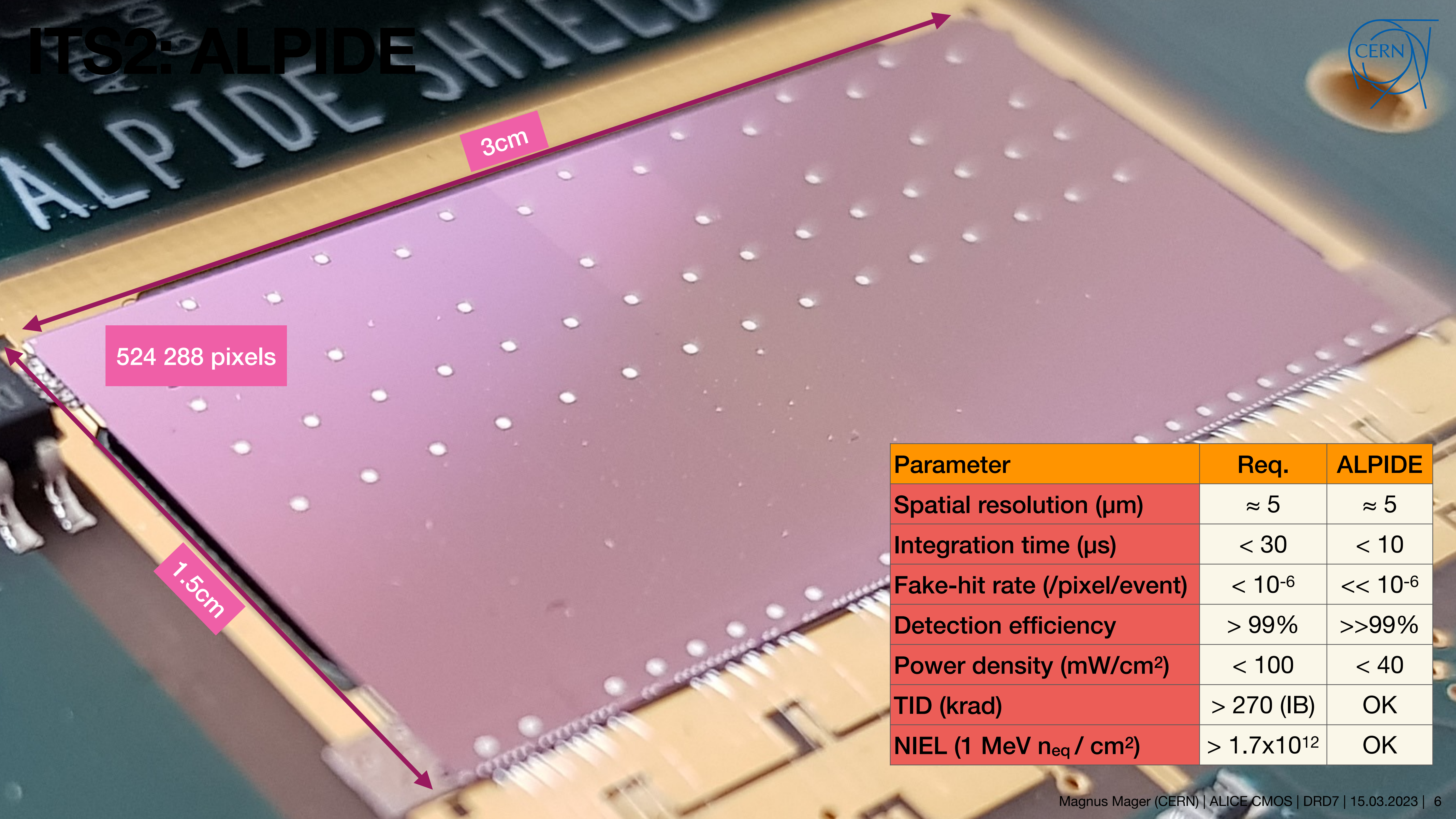
Explorer



pALPIDEss



ITS2: ALPIDE



3cm

524 288 pixels

1.5cm

Parameter	Req.	ALPIDE
Spatial resolution (μm)	≈ 5	≈ 5
Integration time (μs)	< 30	< 10
Fake-hit rate (/pixel/event)	$< 10^{-6}$	$\ll 10^{-6}$
Detection efficiency	$> 99\%$	$\gg 99\%$
Power density (mW/cm^2)	< 100	< 40
TID (krad)	> 270 (IB)	OK
NIEL (1 MeV $n_{\text{eq}} / \text{cm}^2$)	$> 1.7 \times 10^{12}$	OK

ITS2: ALPIDE



3cm

524 288 pixels

> 70k chips produced and tested

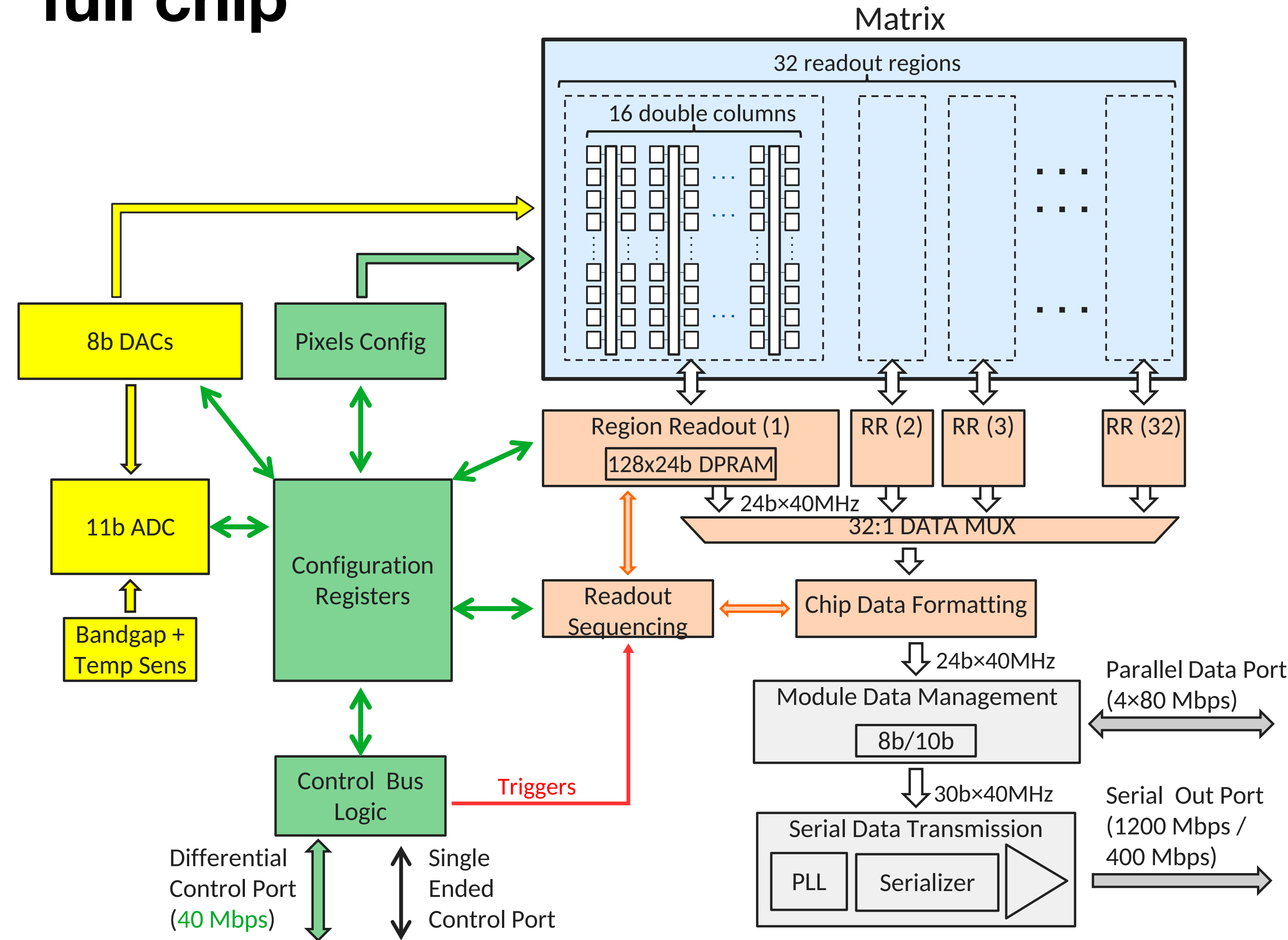
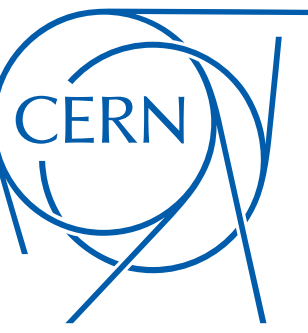
24k in continuous operation on ITS2
+ several other applications

1.5cm

Parameter	Req.	ALPIDE
Spatial resolution (μm)	≈ 5	≈ 5
Integration time (μs)	< 30	< 10
Fake-hit rate (/pixel/event)	$< 10^{-6}$	$\ll 10^{-6}$
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TID (krad)	> 270 (IB)	OK
NIEL ($1 \text{ MeV } n_{\text{eq}} / \text{cm}^2$)	$> 1.7 \times 10^{12}$	OK

ITS2: ALPIDE

full chip



► Fully integrated:

- next active circuit \approx 8 m away off-detector

► Strobing:

- global shutter
- either triggered or in continuous sequence

► Data interface:

- high-speed serial link using copper cables

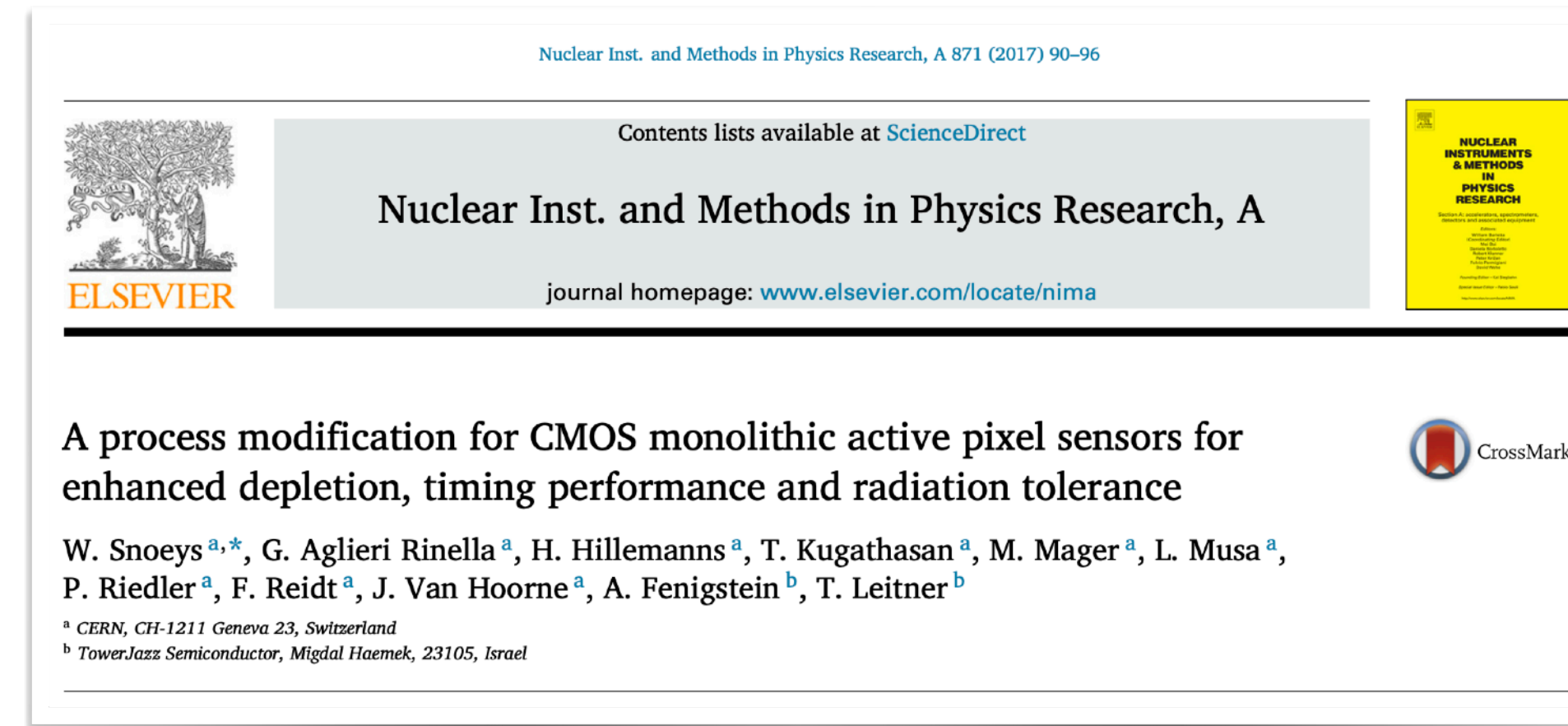
much more than “just” the sensor matrix

ITS2 R&D: process modification

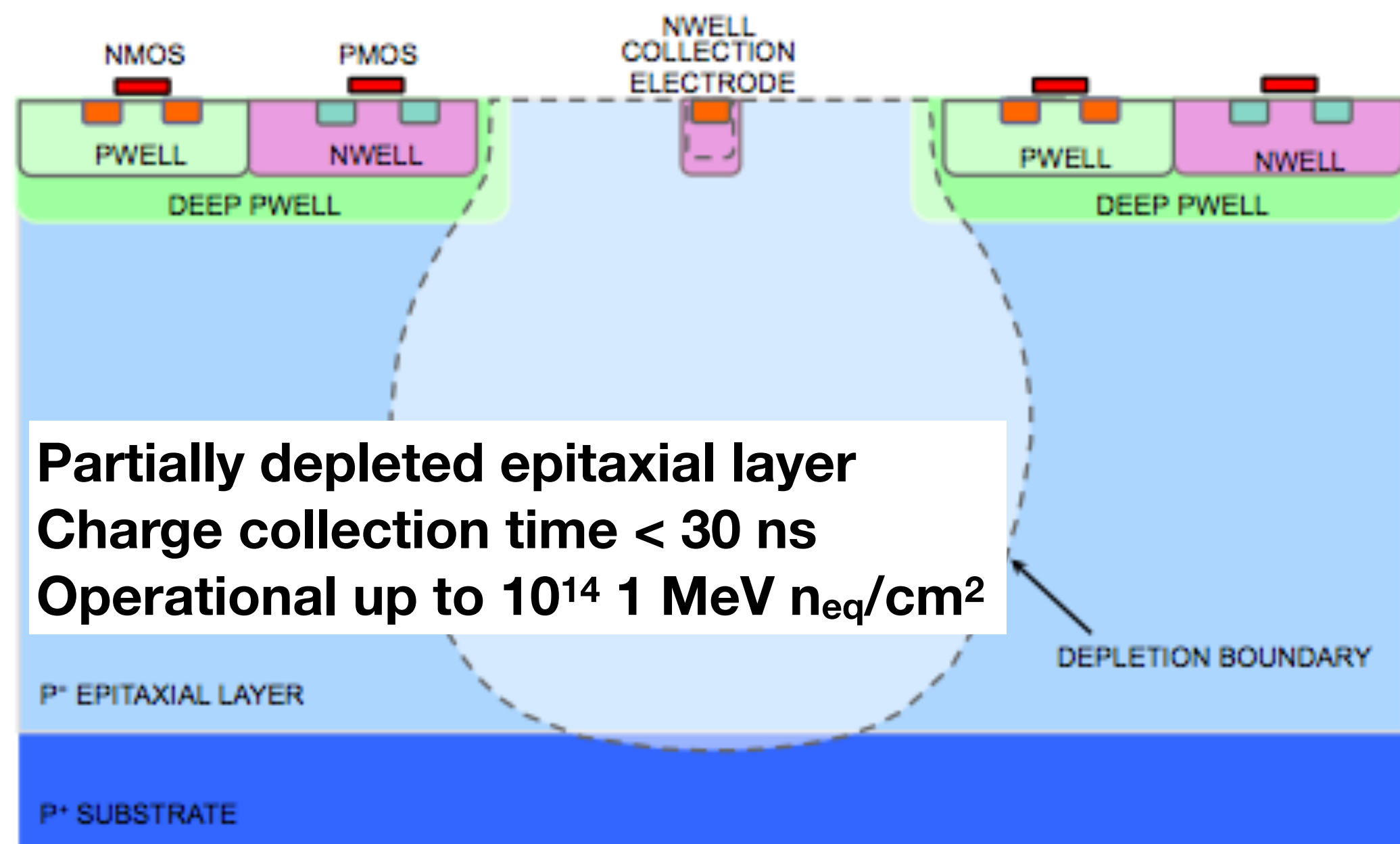


full depletion as “side development”

- ▶ Addition of a **low-dose n-implant**
 - developed together with foundry
- ▶ Opens up new applications
 - higher radiation hardness
 - faster charge collection
- ▶ Now crucial for the 65 nm development (it paid off also for ALICE!)

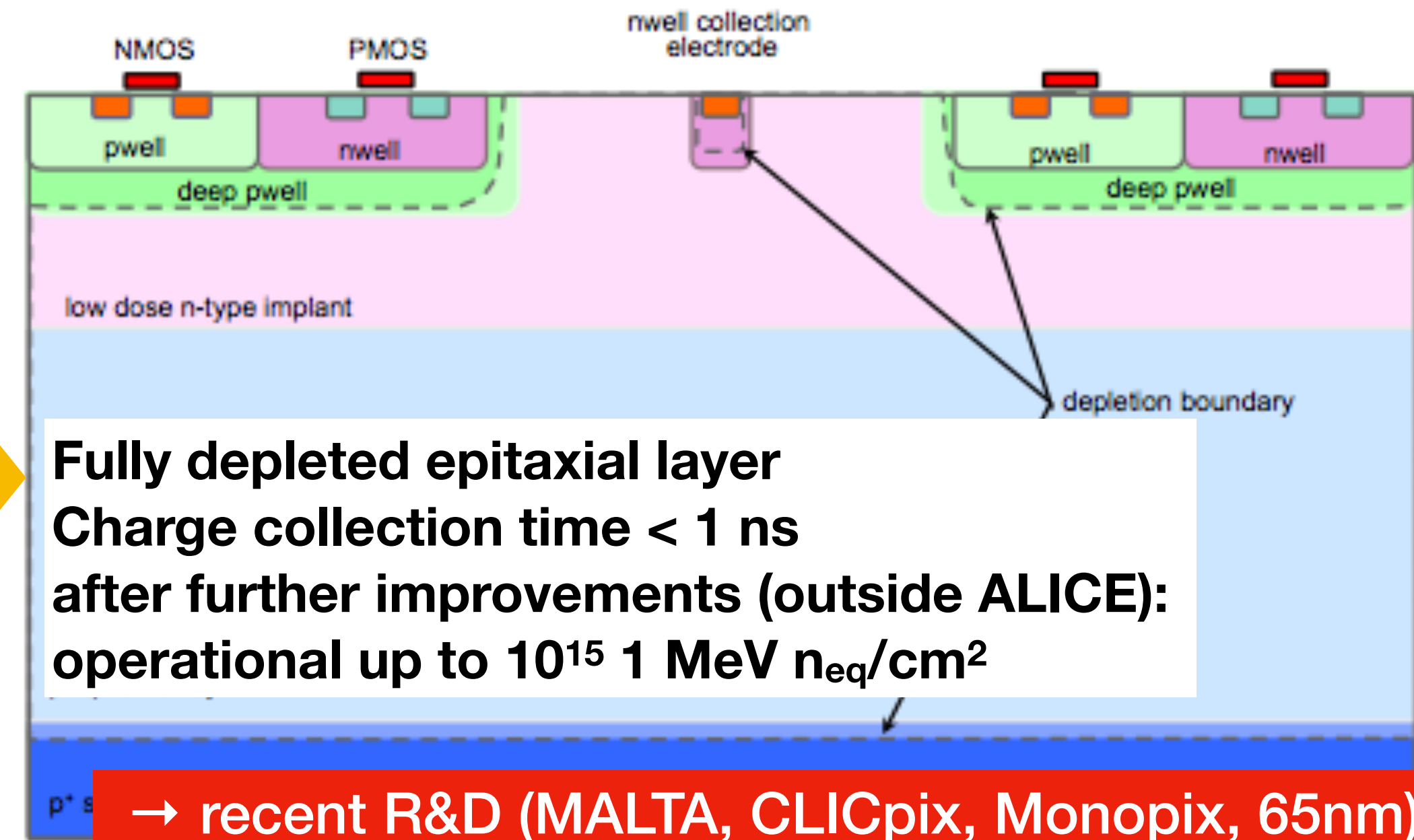


[doi:10.3390/s8095336]



Partially depleted epitaxial layer
Charge collection time < 30 ns
Operational up to 10^{14} 1 MeV n_{eq}/cm^2

Developed and prototyped within ALPIDE R&D

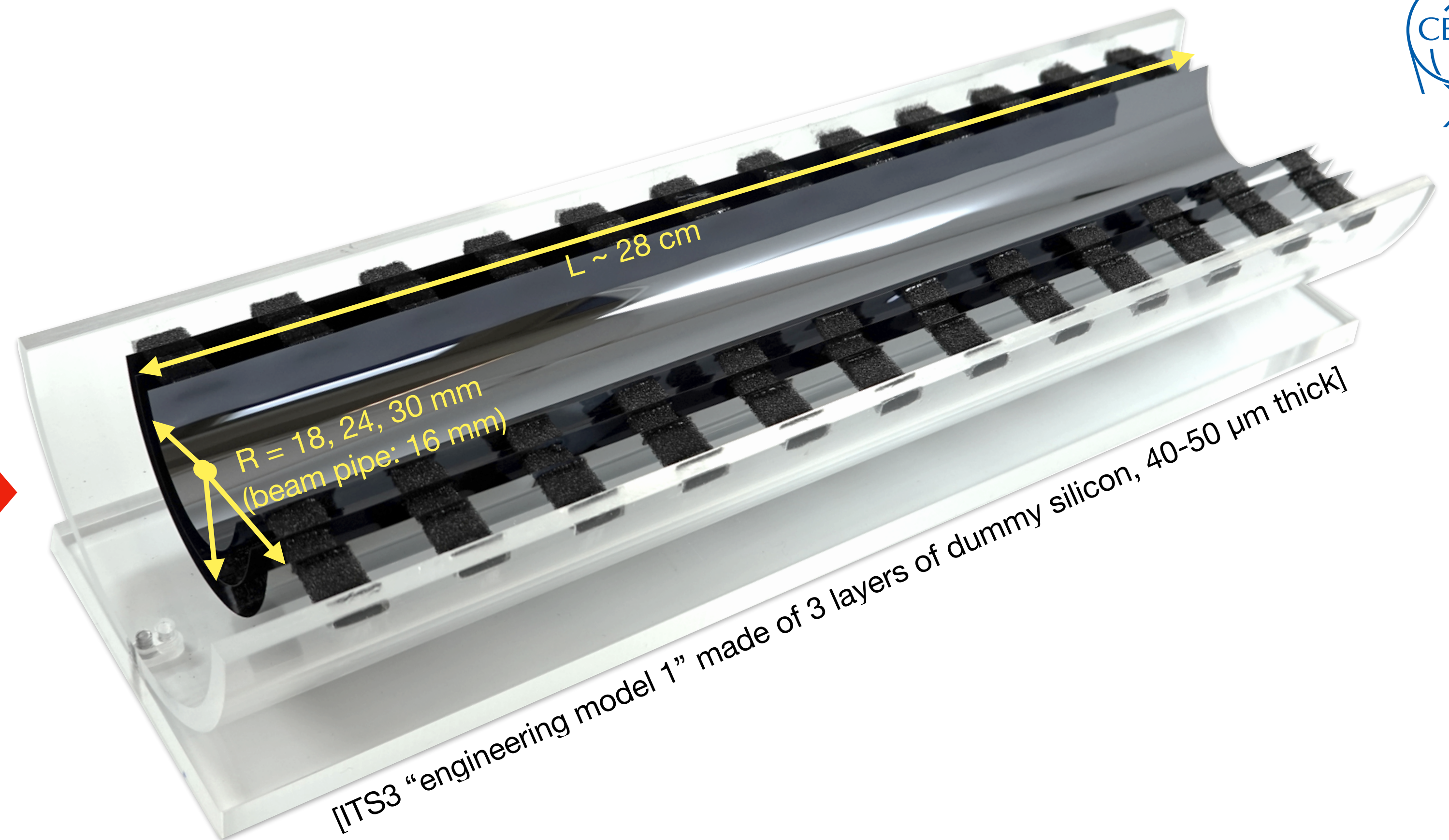
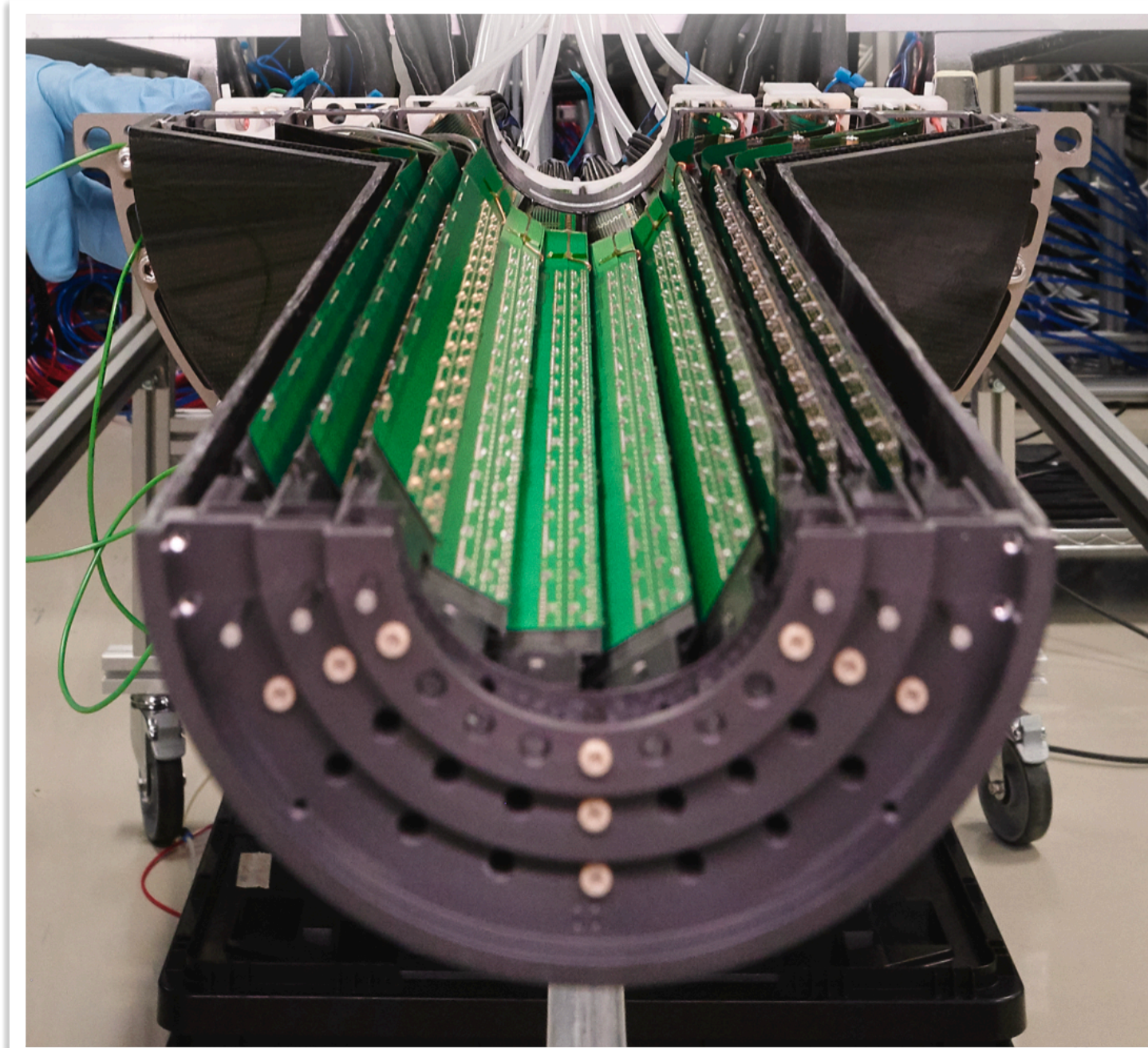


Fully depleted epitaxial layer
Charge collection time < 1 ns
after further improvements (outside ALICE):
operational up to 10^{15} 1 MeV n_{eq}/cm^2

→ recent R&D (MALTA, CLICpix, Monopix, 65nm)

ITS2 → ITS3

the concept



- ▶ Replacing the barrels by real half-cylinders (of **bent, thin** silicon)
- ▶ Rely on **wafer-scale sensors** (1 sensor per half-layer)
- ▶ Minimised material budget and distance to interaction point
→ large improvement of vertexing precision and physics yield ("**ideal detector**")

Relies on the development of wafer-scale sensors

ITS3: 180 nm → 65 nm

qualifying the TPSCo 65 nm CMOS Imaging Technology

▶ Key benefits

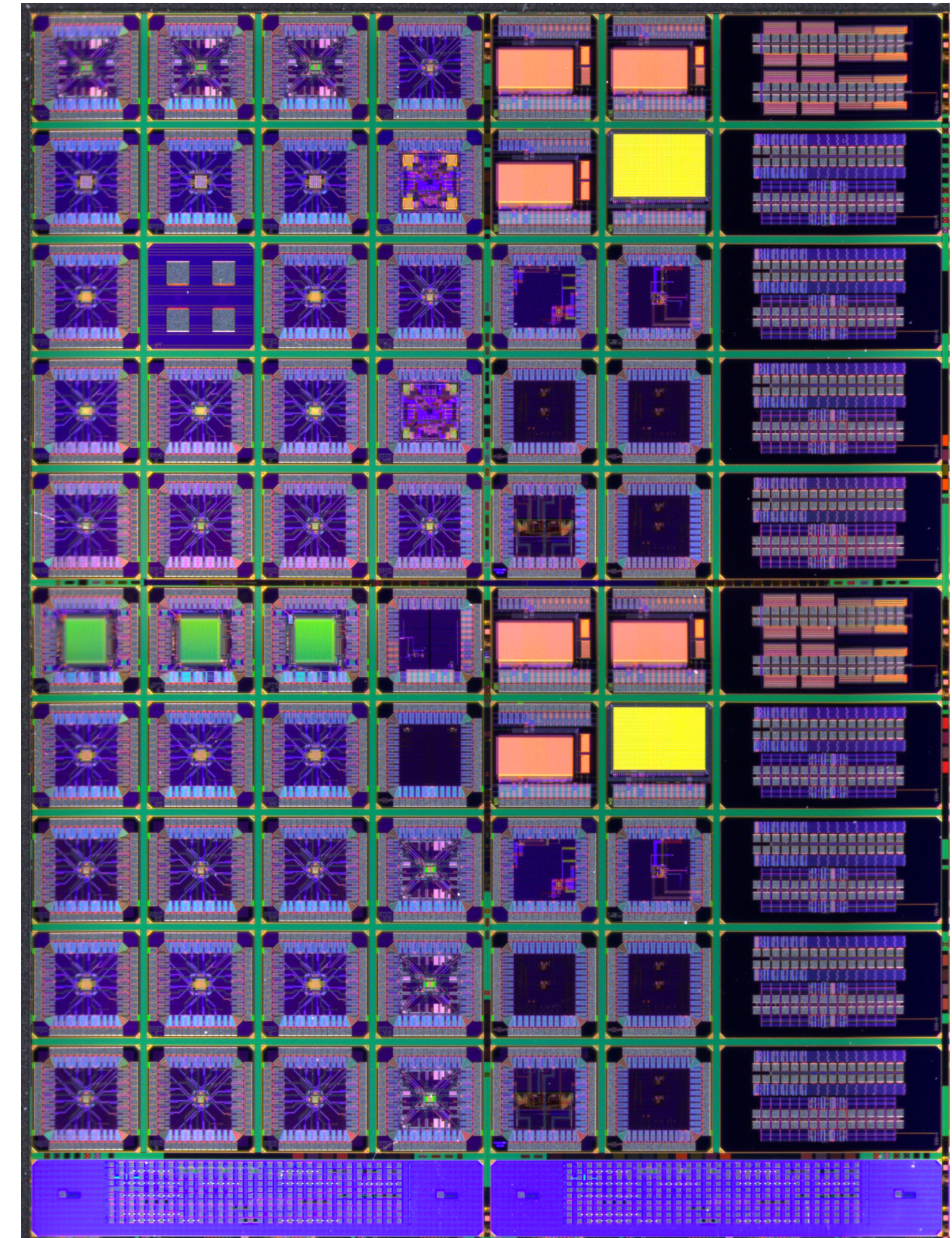
- smaller features/transistors: higher integration density
- smaller pitches
- lower power consumption
- **larger wafers** (200→300 mm)

▶ Similar R&D plan as for 180 nm:

- small prototypes to characterise technology
- then larger chips
- **BUT:** technology node is more advanced, “larger” is larger by 1-2 orders of magnitude (stitching)

▶ MLR1: concentrated effort **ALICE ITS3** together with **CERN EP R&D**

- leverages on experience with 180 nm (ALPIDE)
- excellent links to foundry
- large support from **CERN** (EP department and EP/ESE group)
- Comprehensive *first* submission: **55** prototype chips
- goal: qualify the technology (**achieved**)



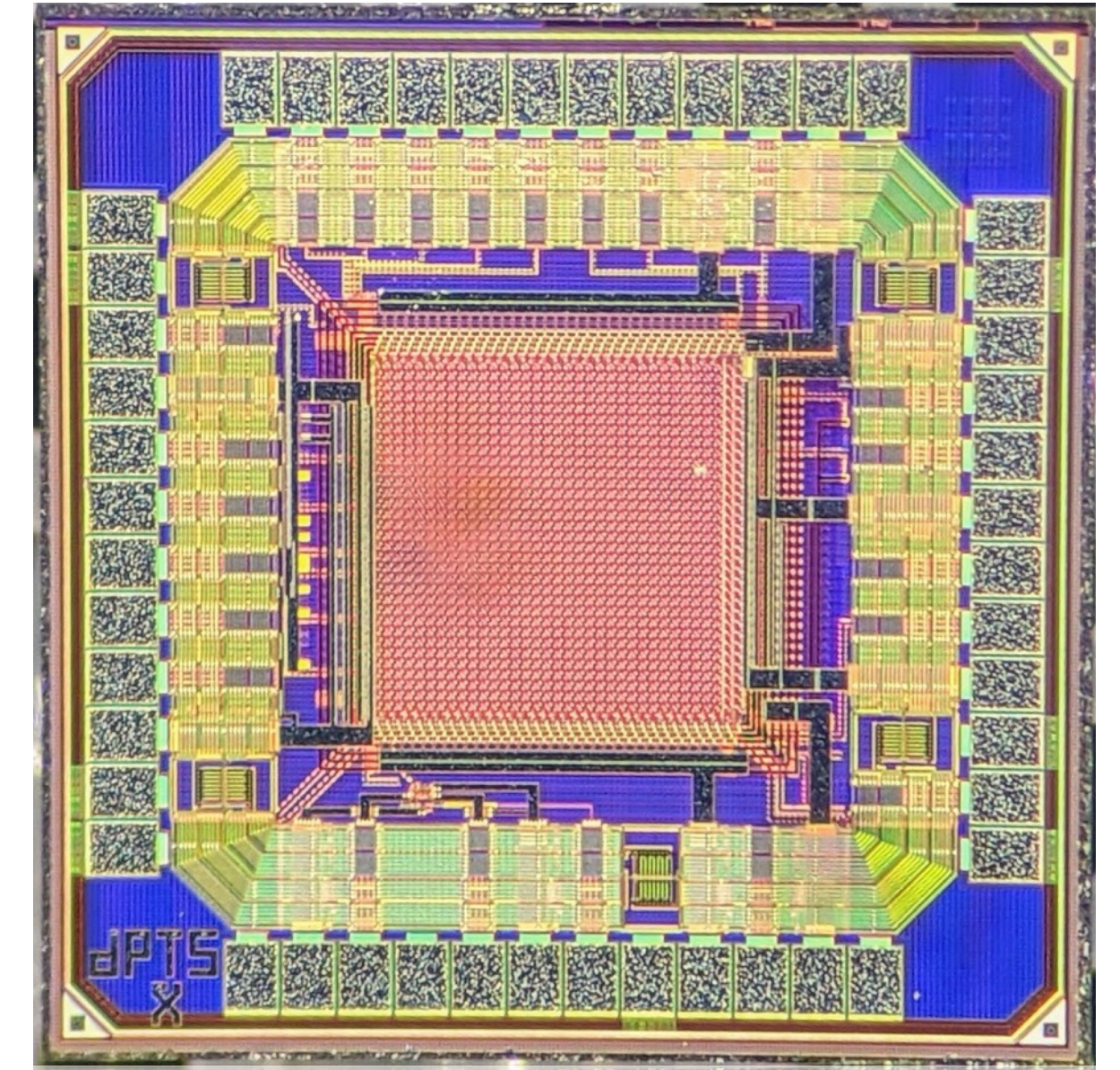
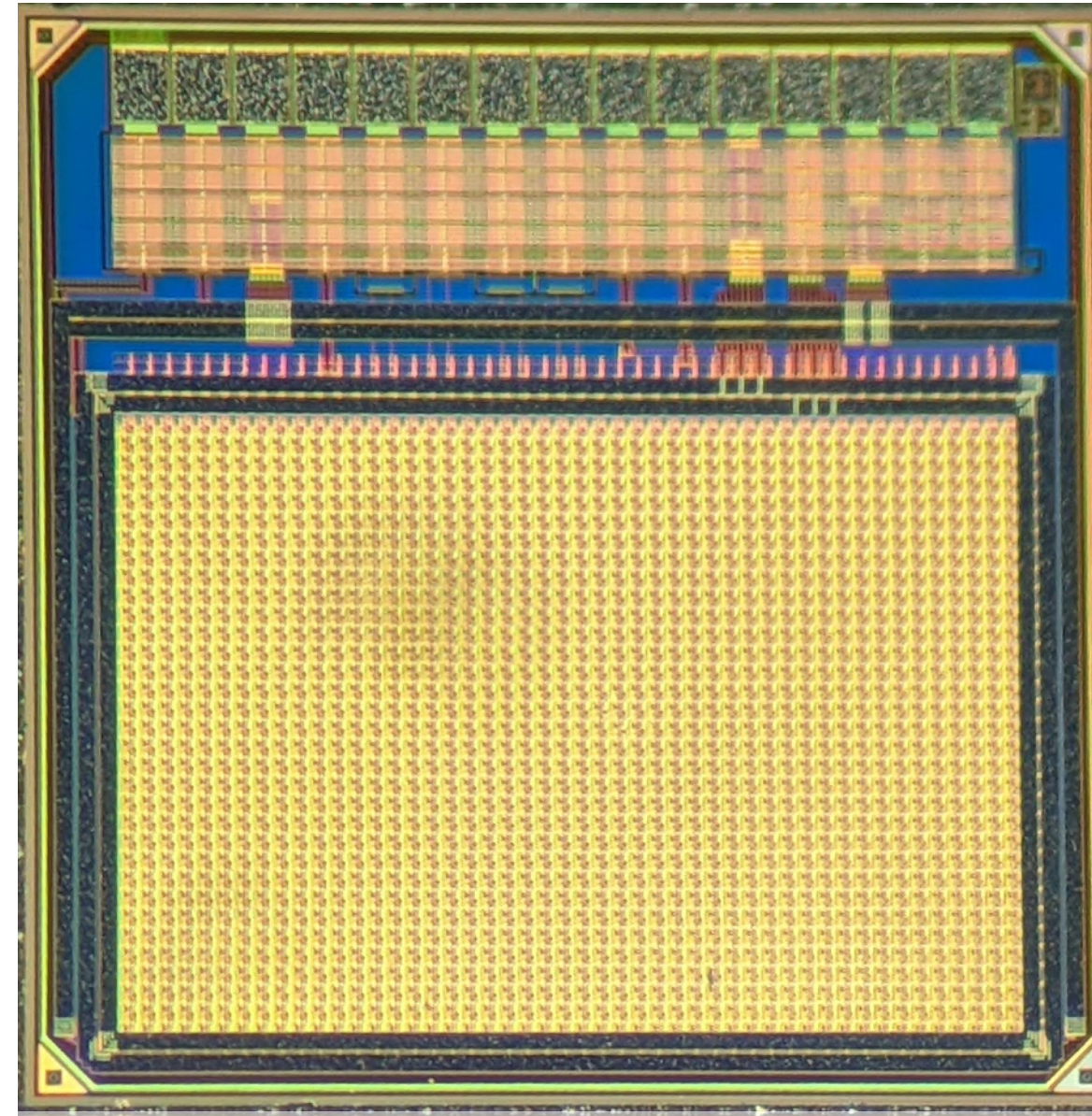
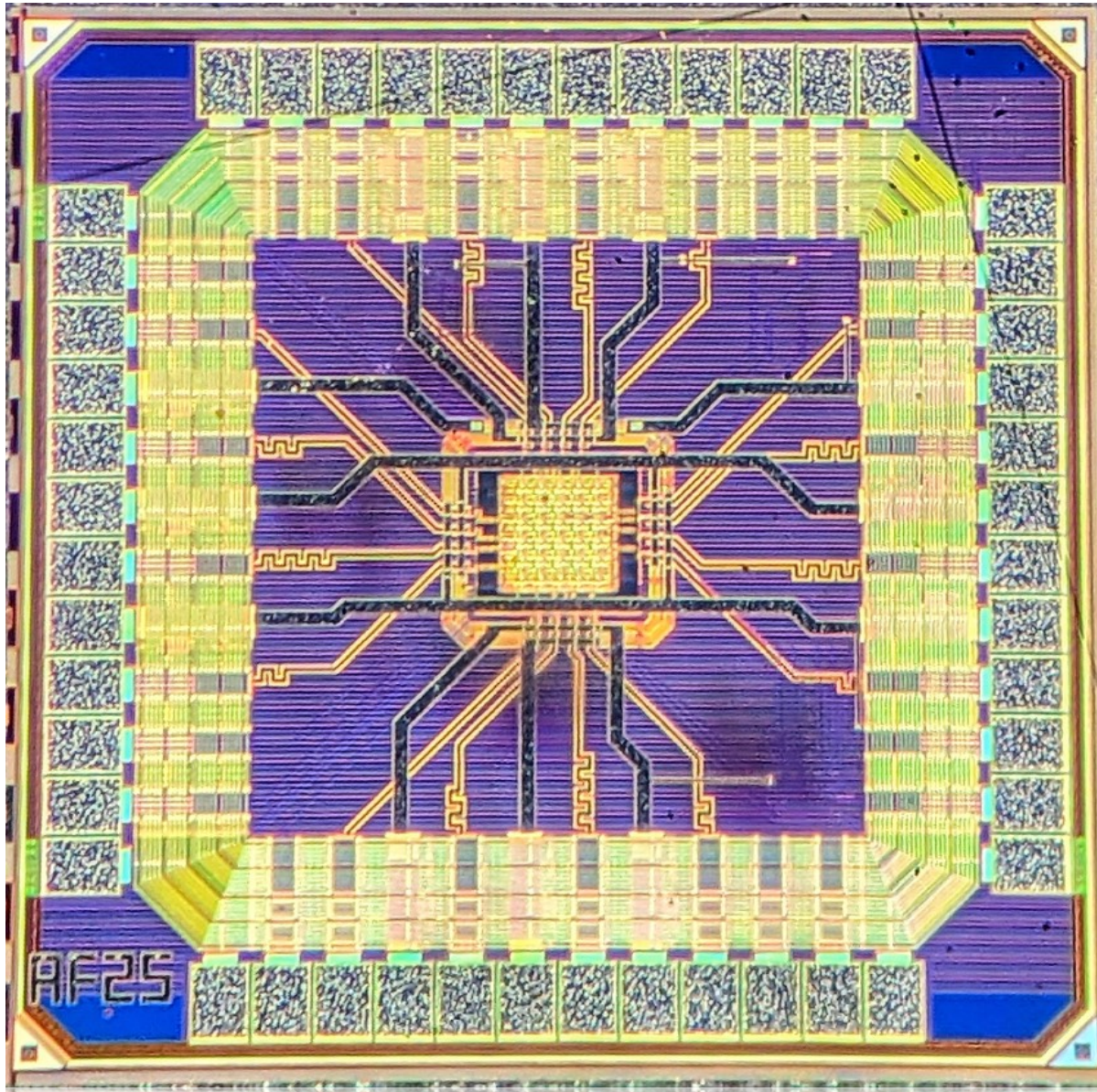
ITS3: pixel prototype chips (selection)

APTS

CE65

DPTS

1.5 mm



- ▶ **matrix:** 6x6 pixels
- ▶ **readout:** direct analog readout of central 4x4
- ▶ **pitch:** 10, 15, 20, 25 μm
- ▶ **total:** 34 dies

- ▶ **matrix:** 64x32, 48x32 pixels
- ▶ **readout:** rolling shutter analog
- ▶ **pitch:** 15, 25 μm
- ▶ **total:** 4 dies

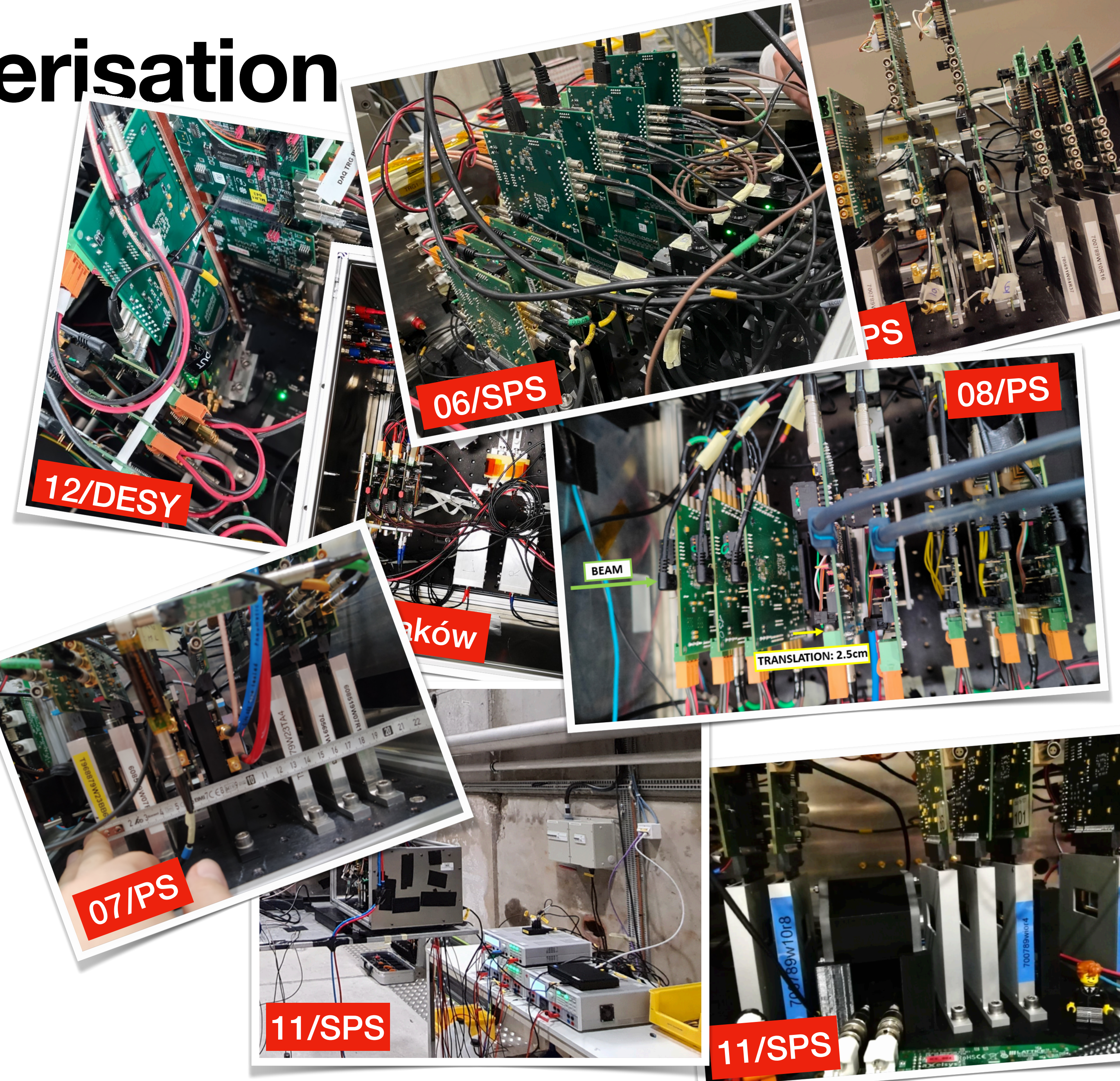
- ▶ **matrix:** 32x32 pixels
- ▶ **readout:** async. digital with ToT
- ▶ **pitch:** 15 μm
- ▶ **total:** 3 dies

Comprehensive set of (small) prototypes and variants to explore the technology for particle detection

ITS3: sensor characterisation

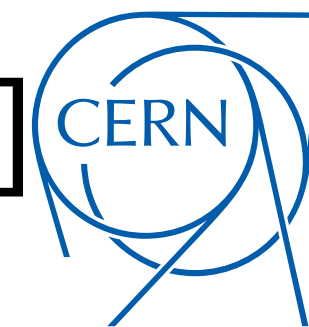
example: test beams

- ▶ Large effort by several ALICE groups
 - groups/links/education
- ▶ Test beams with a cadence of > 1/month
 - several facilities
 - several groups
 - unified test system (in-house, targeted development)
- ▶ comprehensive datasets
 - including less standard configurations (e.g. beam energies)

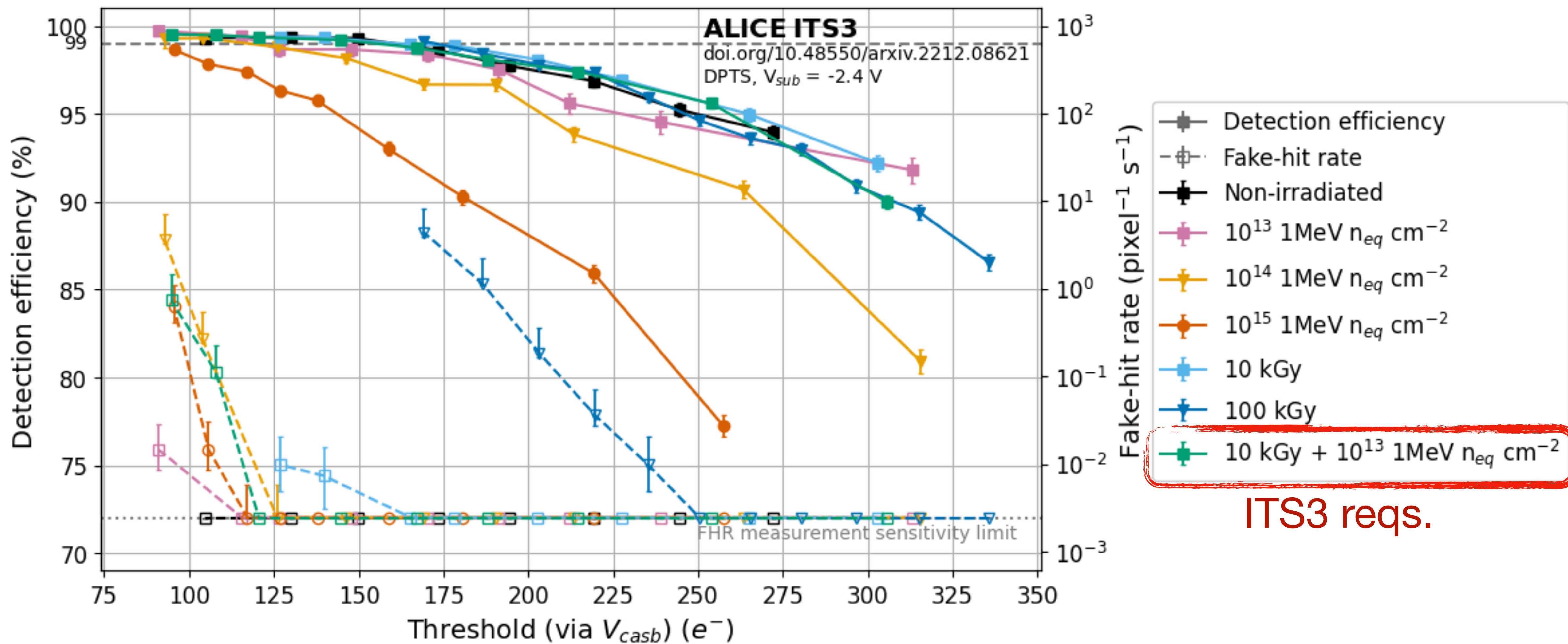


ITS3: DPTS paper (65 nm)

[doi:10.48550/arXiv.2212.08621]



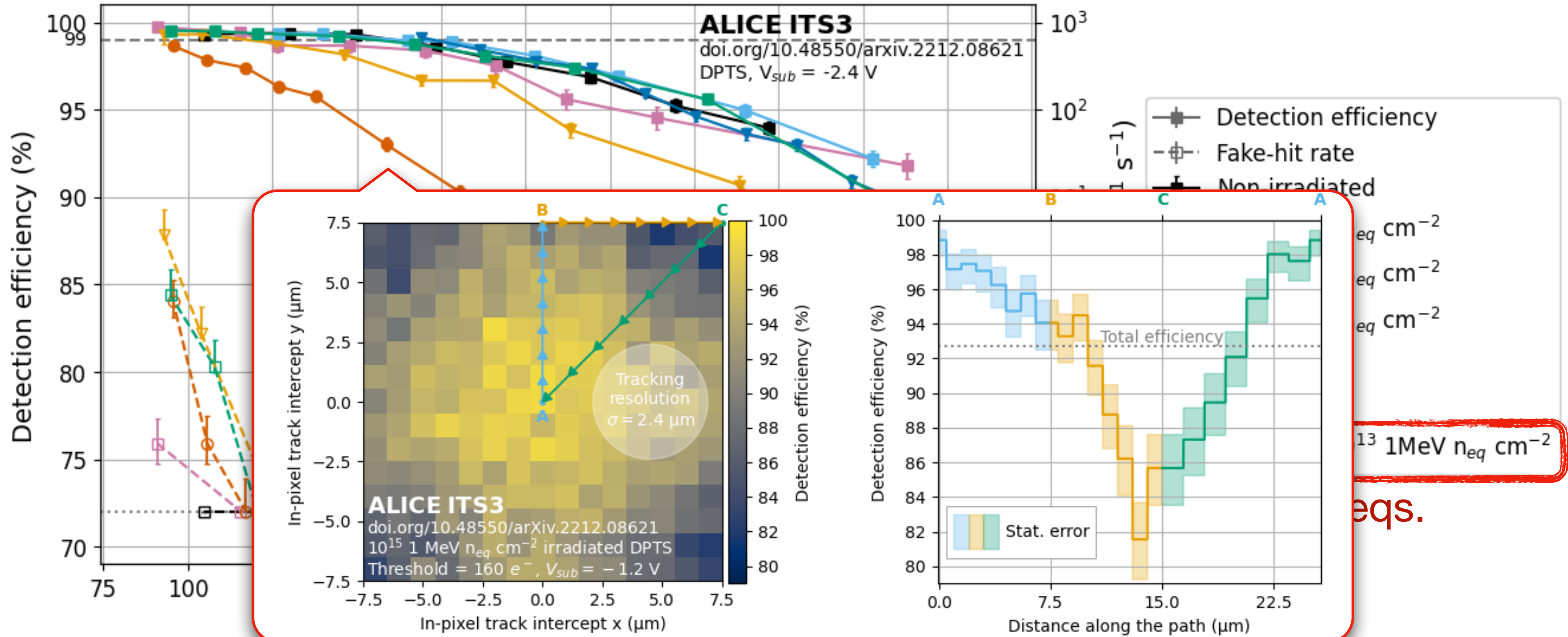
highlights



First comprehensive paper on 65 nm — summarises 1 year of measurements

ITS3: DPTS paper (65 nm)

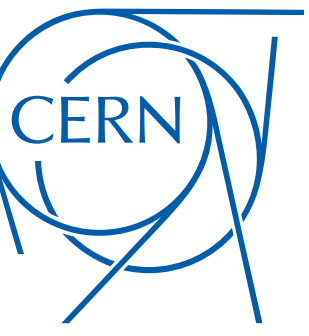
highlights



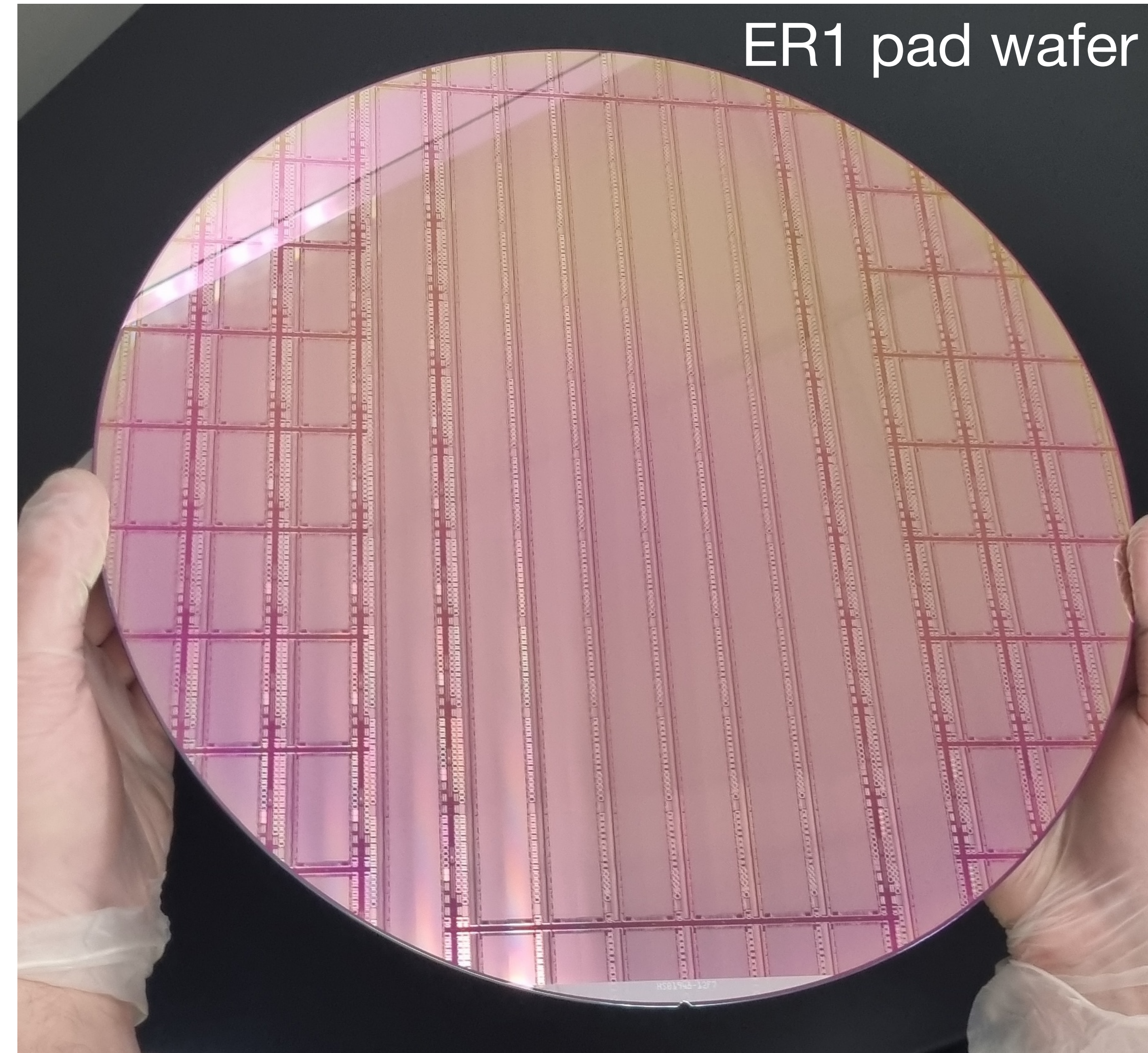
First comprehensive paper on 65 nm — summarises 1 year of measurements

ITS3: Wafer-scale sensors

Engineering Run 1 (ER1)



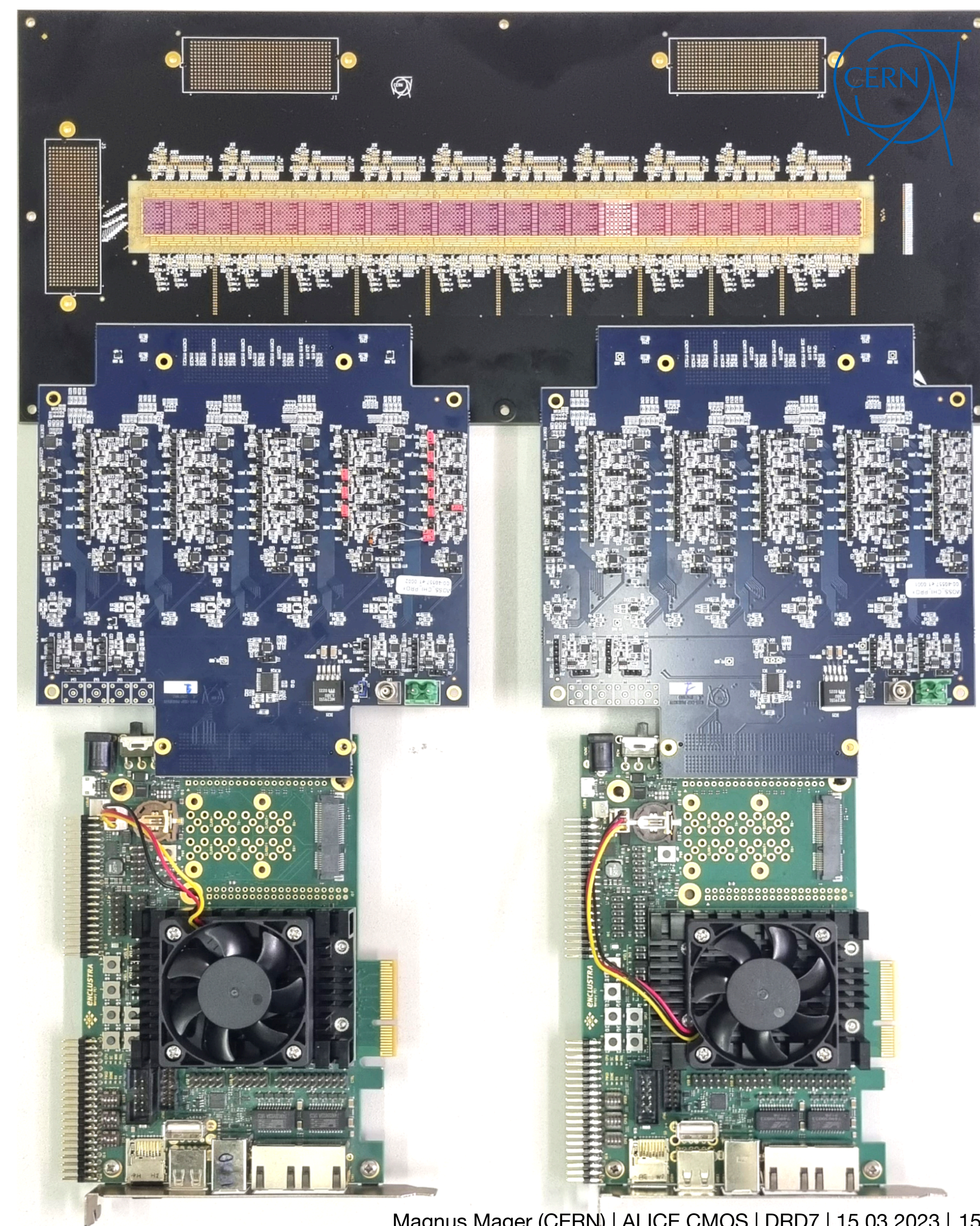
- ▶ Submitted in Dec'22
 - pad wafers: beg. Mar
 - processed wafers: end Mar (tbc)
- ▶ “**MOSS**”: 14 x 259 mm, 6.72 MPixel (22.5 x 22.5 and 18 x 18 μm^2)
 - conservative design, different pitches
- ▶ “**MOST**”: 2.5 x 259 mm, 0.9 MPixel (18 x 18 μm^2)
 - more dense design
- ▶ Plenty of small chips (like MLR1)



ITS3: ER1 testing preparation

MOSS test system

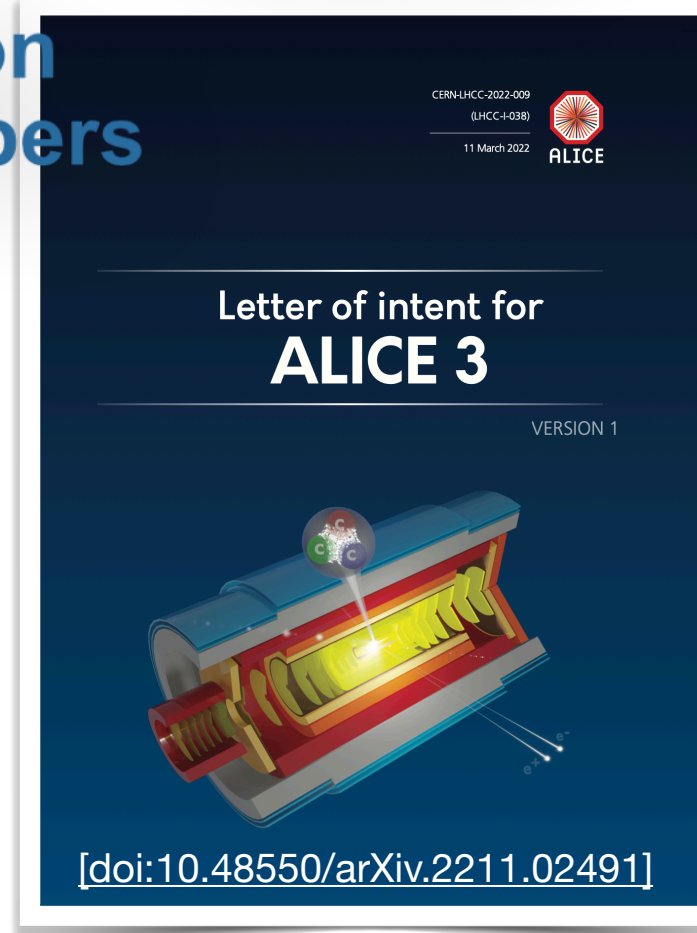
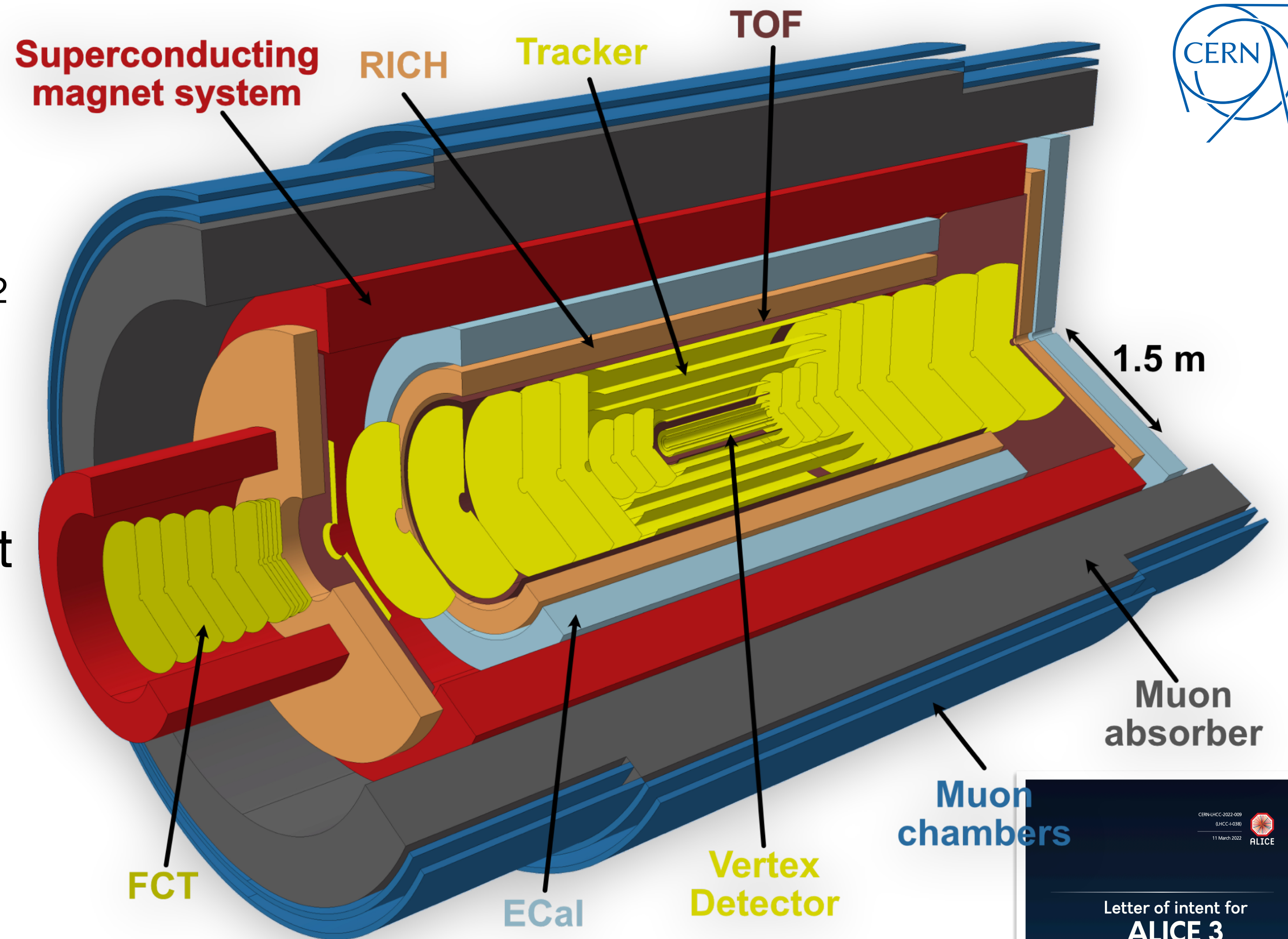
- ▶ In-house development
 - tailored to MOSS chip
- ▶ Based on:
 - carrier card (passive; custom made)
 - 5x proximity card (active; custom made)
 - 5x FPGA board (commercial: enclustra Mercury+ AA1+PE1)
- ▶ Crucial activity involving quite a number of people



ALICE 3

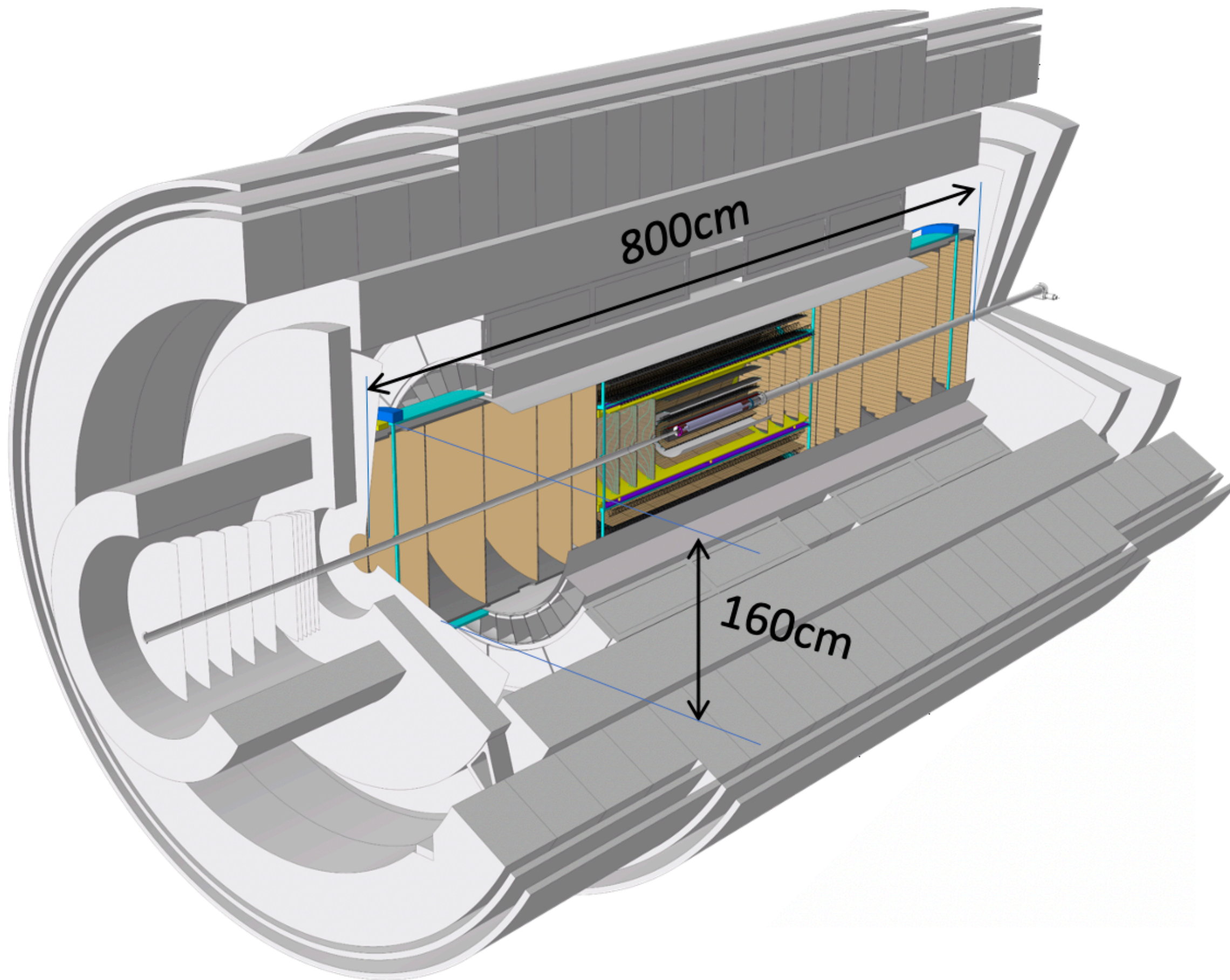
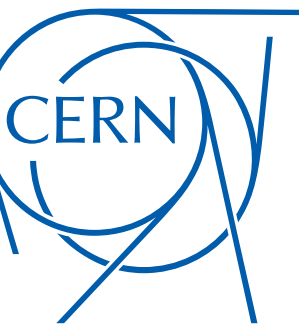
outlook

- ▶ ALICE 3 is centred around a 60 m² MAPS tracker
 - innermost layers will be based on wafer-scale Silicon sensors “iris tracker”, similar to ITS3 (but in vacuum)
 - outer tracker will be based on modules like ITS2 (but order of magnitude larger)
- ▶ Also TOF and RICH based on CMOS technology (baseline)
- ▶ *This is the next big and concrete step for this technology*



ALICE 3

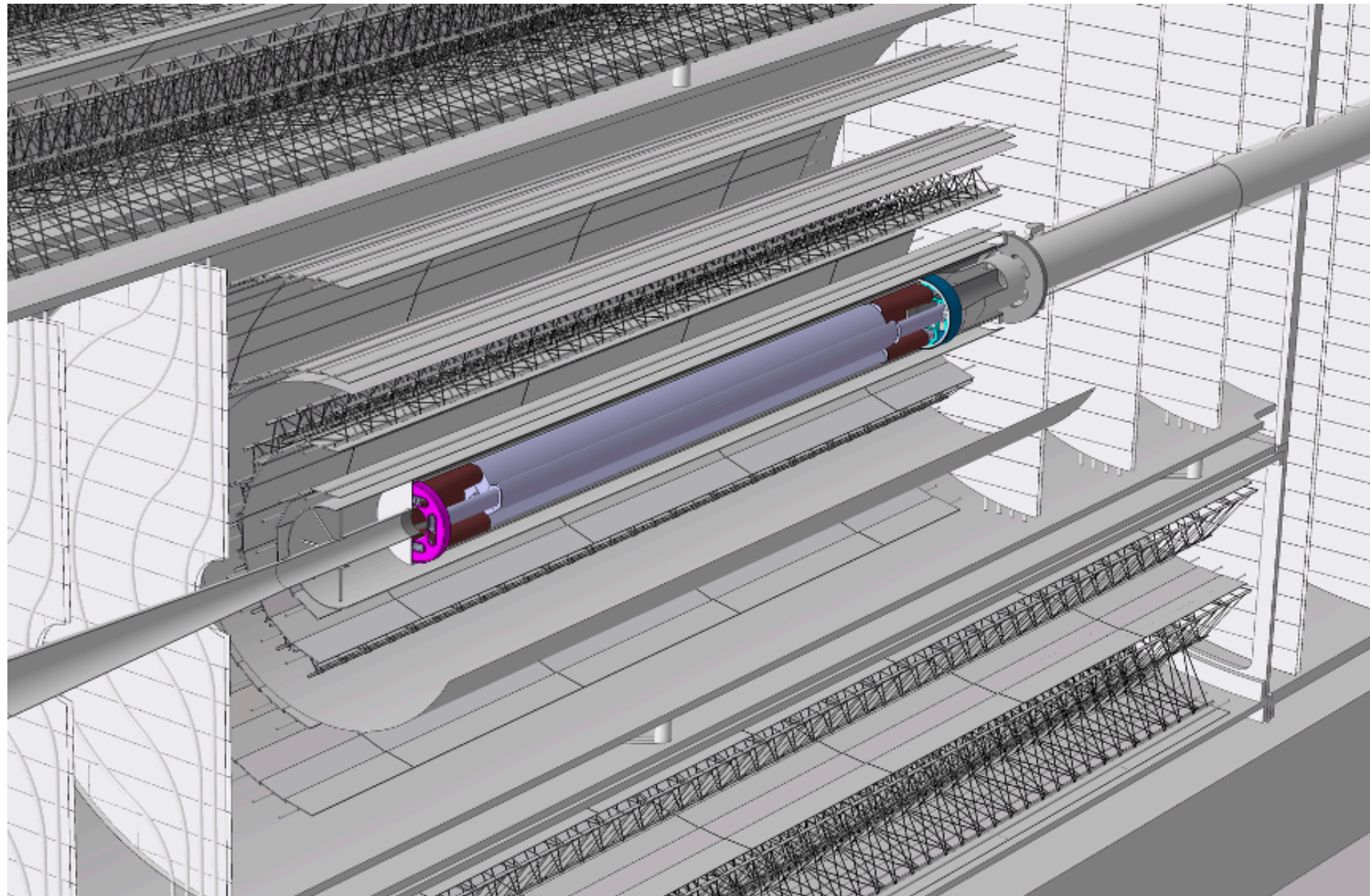
Outer tracker



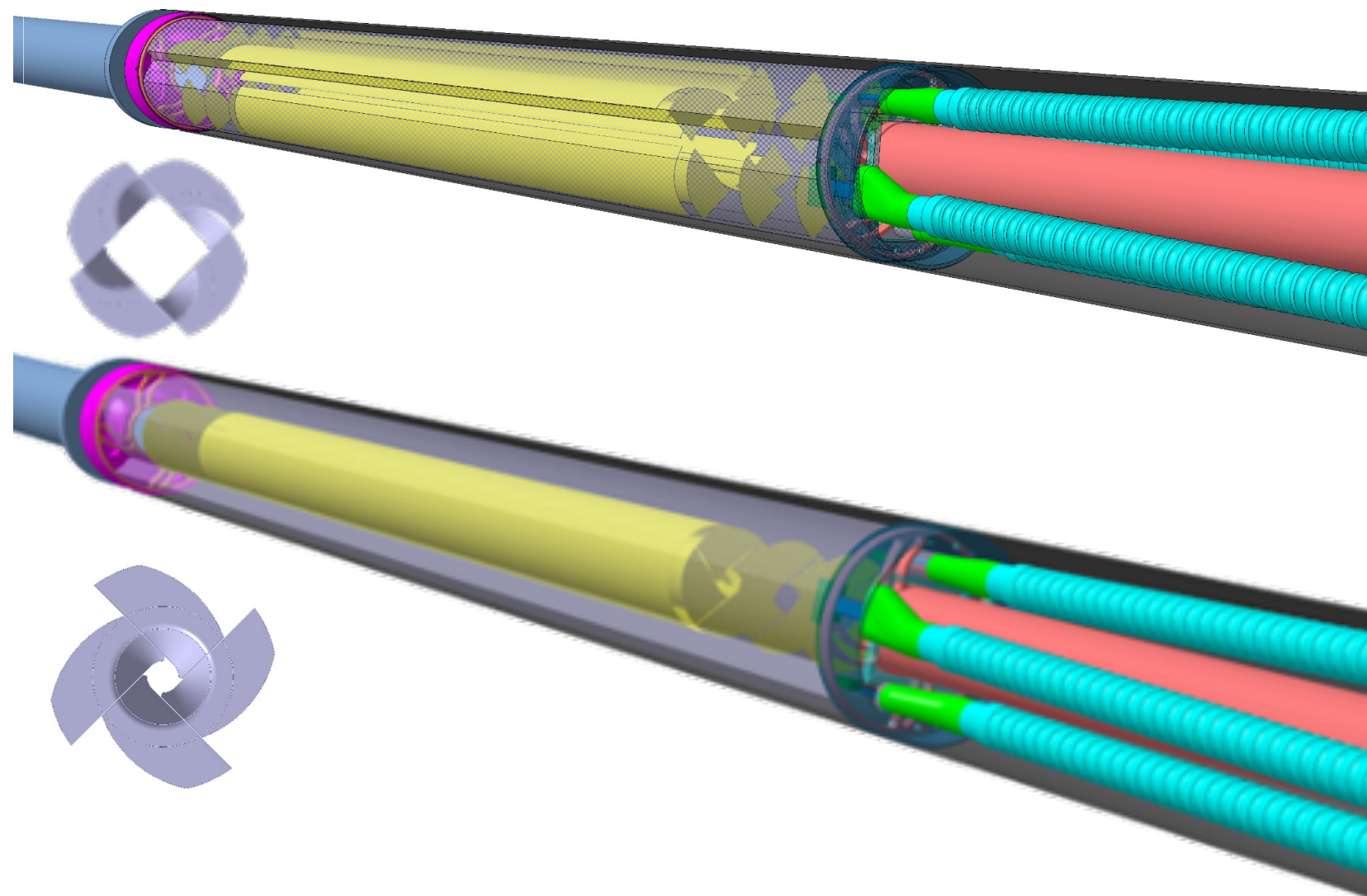
- ▶ **60 m²** silicon pixel detector
 - large coverage: $\pm 4\eta$
 - high-spatial resolution: $\approx 5 \mu\text{m}$
 - very low material budget: X/X_0 (total) $\lesssim 10\%$
 - low power: $\approx 20 \text{ mW/cm}^2$
- ▶ module ($O(10 \times 10 \text{ cm}^2)$) concept based on industry-standard processes for assembly and testing

ALICE 3

Vertex detector

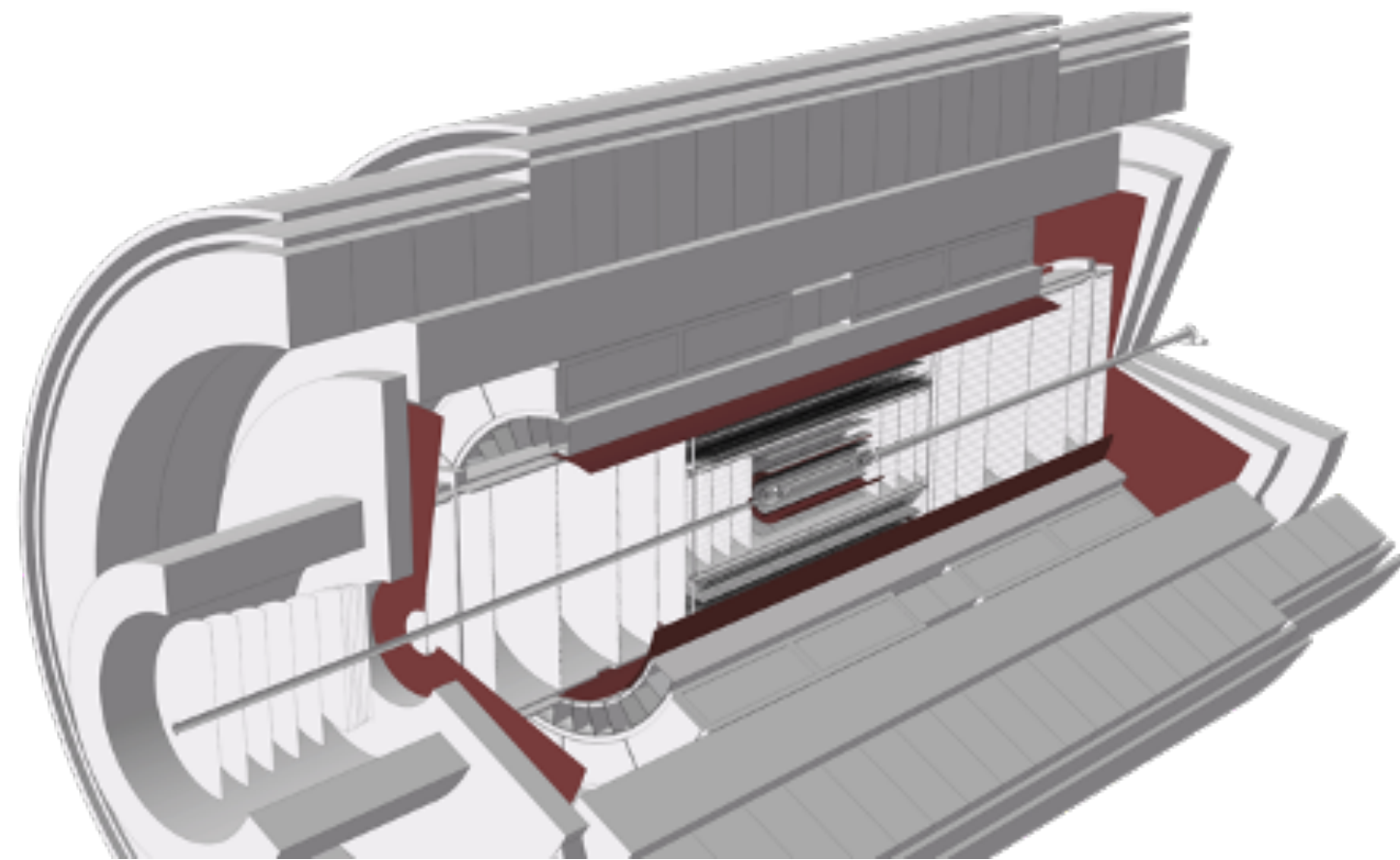
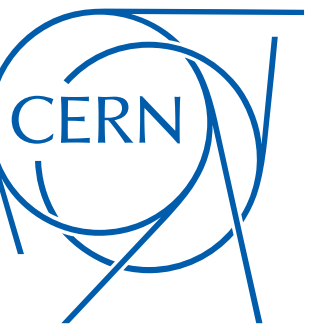


- ▶ Based on **wafer-scale, ultra-thin, curved MAPS**
 - radial distance from interaction point: **5 mm** (inside beampipe, retractable configuration)
 - unprecedented spatial resolution: **$\approx 2.5 \mu\text{m}$**
 - ... and material budget: **$\approx 0.1\% X_0/\text{layer}$**
- ▶ Unprecedented performance figures
 - largely leverages on the ITS3 developments
 - pushes improvements on a number of fronts



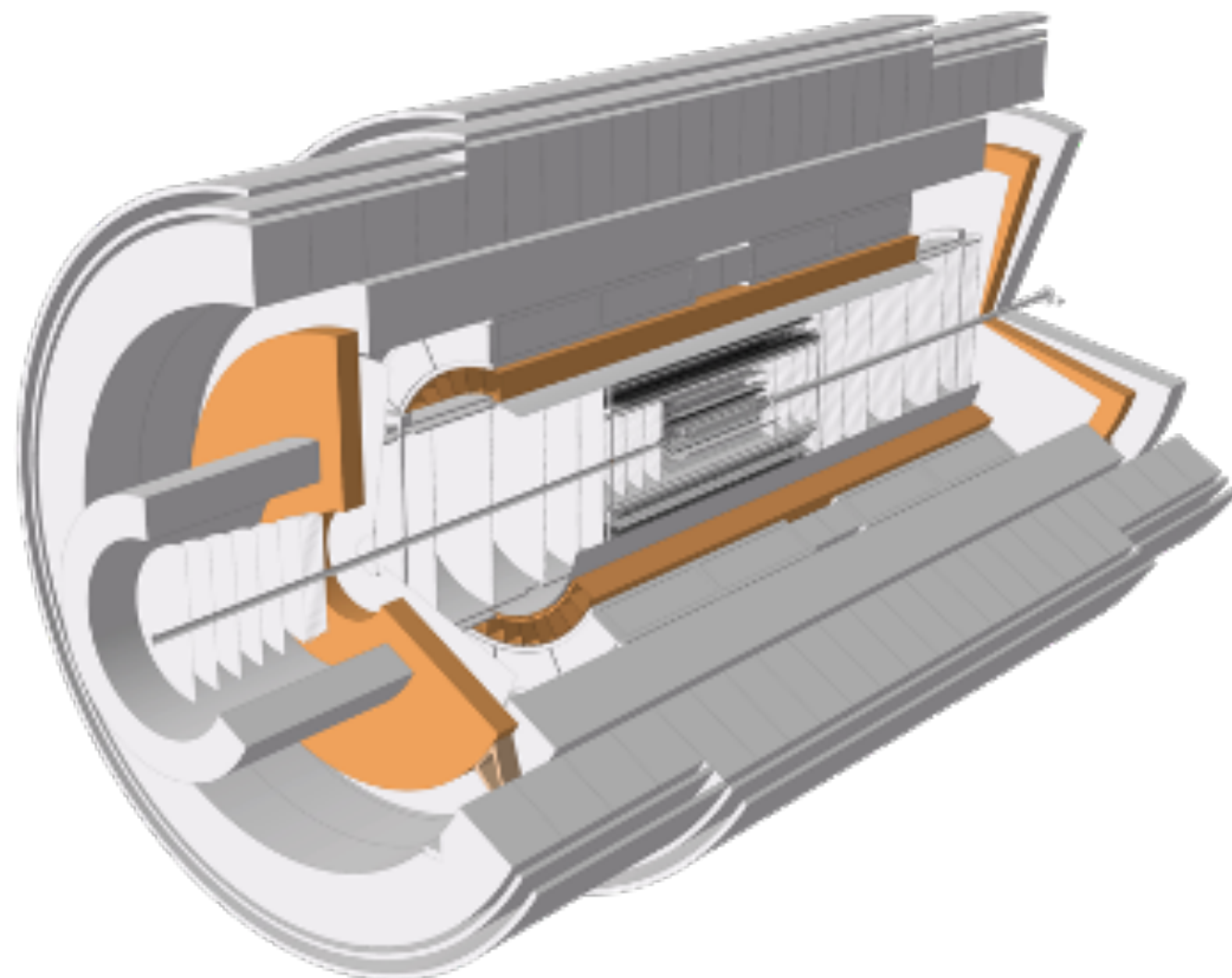
ALICE 3

PID detectors TOF + RICH



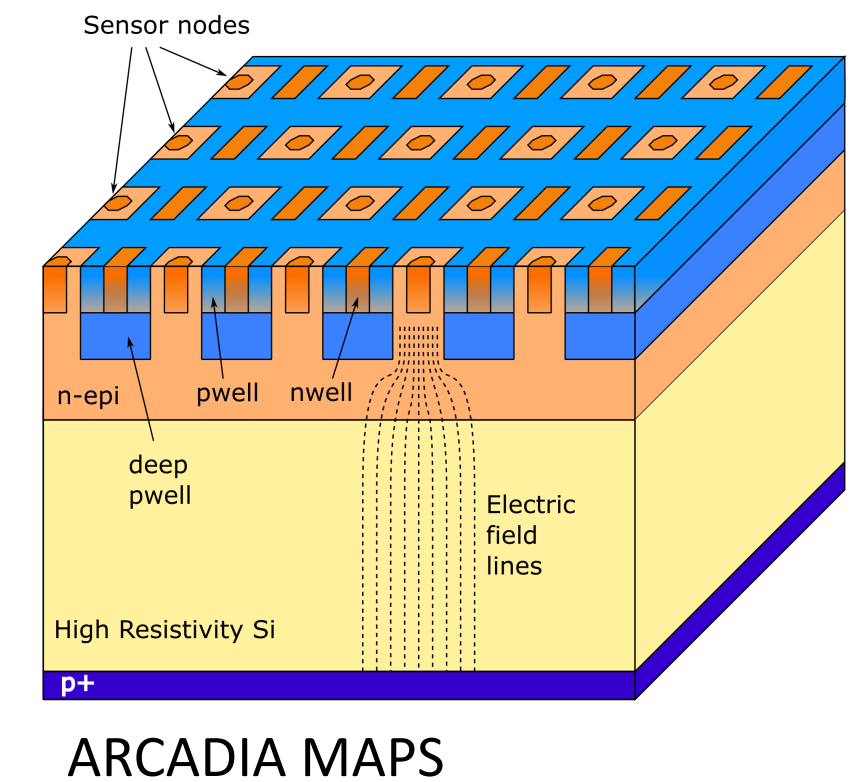
▶ TOF

- surface: $O(45 \text{ m}^2)$
- pitch: 1-5mm pitch
- time resolution: $<20 \text{ ps}$
- CMOS LGADs

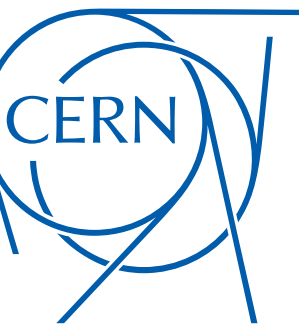


▶ RICH

- $O(50\text{m}^2)$
 - granularity: 3x3 mm
 - digital SiPM (hybrid as fallback)
- ▶ Main benefits in going integrated CMOS:
- cost reduction
 - facilitation of system-level integration



Executive summary



- ▶ **ALICE** is pushing **MAPS** technology since some 10 years:
 - **expertise** in design, characterisation, integration is built up at several institutes within the collaboration
 - **large workforce** >100 people, >20 institutes participate
 - long-standing **relation** with the foundry
- ▶ Driven by clear goals and timelines:
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- ▶ R&D is exploring the technology far beyond the strict ALICE needs:
 - e.g. using process options to improve on radiation hardness and timing performance
 - gives a lot of **confidence** for the concrete ALICE application, **serves** the community as a whole, and also paves the way for the **future** ALICE plans
 - ALICE follows an inclusive approach (open non-ALICE members welcome)

significant support from CERN EP department and EP-ESE group!
- ▶ Developed technology is used for several **off-spring** experiments (HEP, medical, ...)
 - several (smaller, but not necessarily small) experiments have adopted ALPIDE
 - 180 nm technology is now widely used

→ now Frederic's talk for technical details!

Thank you!

